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• Bociort, Florian

2624 CV Delft (NL)

• Braat, Josephus Johannes Maria

2627 CA Delft (NL)

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(71) Applicant: ASM LITHOGRAPHY B.V.
5503 LA Veldhoven (NL)

(74) Representative: Leeming, John Gerard

J.A. Kemp & Co.,

14 South Square,

Gray's Inn

London WC1R 5LX (GB)

(72) Inventors:

• Bal, Matthieu Frederic
2628 TB Delft (NL)

(54) Lithographic apparatus and device manufacturing method

(57) A classification system for systems of n mirrors, whereby systems of mirrors are classified by a number C , is defined as follows:

$$C = \sum_{i=1}^n a_i \cdot 2^{(n-i)} \left(\frac{M}{|M|} \right)$$

where:

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,

$a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,

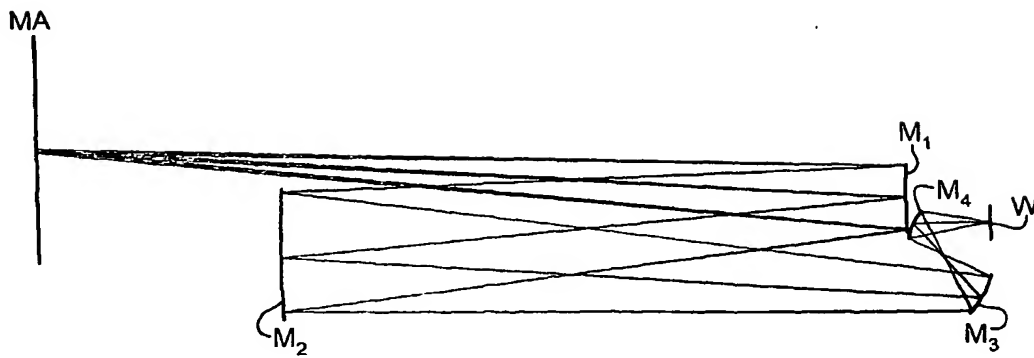
M is the magnification of the projection system, and index i numbers the mirrors of the system in series.

Four mirror systems in classes 2(-), 6(-), or 9(-), six mirror systems in classes 5(+), 6(-), 9(+), 13(+), 18(-), 21(+), 22(-), 25(+), 29(+), 34(-), 37(+), 38(-), 42(-), and 54(-) where (+) and (-) respectively indicate that the overall magnification of the system is positive or negative, and eight mirror systems in class 2(+), 5(+), 9(+),

12(+), 13(+), 18(+), 18(-), 19(+), 20(+), 21(+), 22(+), 23(+), 25(+), 26(+), 34(-), 36(+), 37(+), 38(-), 45(+), 46(+), 49(+), 52(+), 53(+), 54(+), 54(-), 55(-), 58(-), 68(+), 69(+), 73(+), 74(+), 77(+), 82(+), 82(-), 85(+), 88(+), 89(+), 90(-), 92(+), 93(+), 97(+), 100(-), 101(+), 102(-), 104(+), 105(+), 106(+), 106(-), 107(+), 108(+), 109(+), 109(-), 110(+), 110(-), 111(+), 113(+), 116(+), 117(+), 118(+), 118(-), 120(+), 121(+), 122(-), 123(-), 132(+), 133(+), 134(-), 137(+), 138(+), 141(+), 145(+), 145(-), 146(+), 146(-), 147(+), 148(+), 148(-), 149(+), 150(+), 150(-), 151(+), 151(-), 152(-), 153(+), 154(+), 154(-), 155(+), 155(-), 156(+), 157(+), 159(+), 161(+), 162(-), 163(-), 164(+), 165(+), 166(+), 166(-), 167(+), 168(+), 169(+), 170(+), 170(-), 171(+), 172(+), 173(+), 174(+), 175(+), 176(+), 177(+), 178(-), 179(+), 180(+), 180(-), 181(+), 181(-), 182(+), 182(-), 183(+), 183(-), 184(+), 185(+), 185(-), 186(-), 187(+), 187(-), 188(-), 189(+), 196(+), 197(+), 201(+), 203(+), 205(+), 209(+), 214(-), 216(+), 217(+), 218(+), 218(-), 225(+), 228(+), 229(+), 230(+), 232(+), 233(+), 235(+), 236(+), 237(+), 238(-), 243(+), 246(+), 247(+), 248(+), 250(-), are useful in EUV lithography projection systems.

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Fig. 6



Description

[0001] The present invention relates to a lithographic projection apparatus comprising:

- a radiation system for supplying a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate; and
- a projection system for projecting the patterned beam onto a target portion of the substrate.

[0002] The term "patterning means" as here employed should be broadly interpreted as referring to means that can be used to endow an incoming radiation beam with a patterned cross-section, corresponding to a pattern that is to be created in a target portion of the substrate; the term "light valve" can also be used in this context. Generally, the said pattern will correspond to a particular functional layer in a device being created in the target portion, such as an integrated circuit or other device (see below). Examples of such patterning means include:

- A mask. The concept of a mask is well known in lithography, and it includes mask types such as binary, alternating phase-shift, and attenuated phase-shift, as well as various hybrid mask types. Placement of such a mask in the radiation beam causes selective transmission (in the case of a transmissive mask) or reflection (in the case of a reflective mask) of the radiation impinging on the mask, according to the pattern on the mask. In the case of a mask, the support structure will generally be a mask table, which ensures that the mask can be held at a desired position in the incoming radiation beam, and that it can be moved relative to the beam if so desired.
- A programmable mirror array. An example of such a device is a matrix-addressable surface having a viscoelastic control layer and a reflective surface. The basic principle behind such an apparatus is that (for example) addressed areas of the reflective surface reflect incident light as diffracted light, whereas unaddressed areas reflect incident light as undiffracted light. Using an appropriate filter, the said undiffracted light can be filtered out of the reflected beam, leaving only the diffracted light behind; in this manner, the beam becomes patterned according to the addressing pattern of the matrix-addressable surface. The required matrix addressing can be performed using suitable electronic means. More information on such mirror arrays can be gleaned, for example, from United States Patents US 5,296,891 and US 5,523,193, which are incorporated herein by reference. In the case of a programmable mirror array, the said support structure may be embodied as a frame or table, for example, which may be fixed or movable as required.
- A programmable LCD array. An example of such a construction is given in United States Patent US 5,229,872, which is incorporated herein by reference. As above, the support structure in this case may be embodied as a frame or table, for example, which may be fixed or movable as required.

For purposes of simplicity, the rest of this text may, at certain locations, specifically direct itself to examples involving a mask and mask table; however, the general principles discussed in such instances should be seen in the broader context of the patterning means as hereabove set forth.

[0003] Lithographic projection apparatus can be used, for example, in the manufacture of integrated circuits (ICs). In such a case, the patterning means may generate a circuit pattern corresponding to an individual layer of the IC, and this pattern can be imaged onto a target portion (e.g. comprising one or more dies) on a substrate (silicon wafer) that has been coated with a layer of radiation-sensitive material (resist). In general, a single wafer will contain a whole network of adjacent target portions that are successively irradiated via the projection system, one at a time. In current apparatus, employing patterning by a mask on a mask table, a distinction can be made between two different types of machine. In one type of lithographic projection apparatus, each target portion is irradiated by exposing the entire mask pattern onto the target portion in one go; such an apparatus is commonly referred to as a wafer stepper. In an alternative apparatus — commonly referred to as a step-and-scan apparatus — each target portion is irradiated by progressively scanning the mask pattern under the projection beam in a given reference direction (the "scanning" direction) while synchronously scanning the substrate table parallel or anti-parallel to this direction; since, in general, the projection system will have a magnification factor M (generally < 1), the speed V at which the substrate table is scanned will be a factor M times that at which the mask table is scanned. More information with regard to lithographic devices as here described can be gleaned, for example, from US 6,046,792, incorporated herein by reference.

[0004] In a manufacturing process using a lithographic projection apparatus, a pattern (e.g. in a mask) is imaged onto a substrate that is at least partially covered by a layer of radiation-sensitive material (resist). Prior to this imaging step, the substrate may undergo various procedures, such as priming, resist coating and a soft bake. After exposure, the substrate may be subjected to other procedures, such as a post-exposure bake (PEB), development, a hard bake and measurement/inspection of the imaged features. This array of procedures is used as a basis to pattern an individual

layer of a device, e.g. an IC. Such a patterned layer may then undergo various processes such as etching, ion-implantation (doping), metallization, oxidation, chemo-mechanical polishing, etc., all intended to finish off an individual layer. If several layers are required, then the whole procedure, or a variant thereof, will have to be repeated for each new layer. Eventually, an array of devices will be present on the substrate (wafer). These devices are then separated from one another by a technique such as dicing or sawing, whence the individual devices can be mounted on a carrier, connected to pins, etc. Further information regarding such processes can be obtained, for example, from the book "Microchip Fabrication: A Practical Guide to Semiconductor Processing", Third Edition, by Peter van Zant, McGraw Hill Publishing Co., 1997, ISBN 0-07-067250-4, incorporated herein by reference.

[0005] For the sake of simplicity, the projection system may hereinafter be referred to as the "lens"; however, this term should be broadly interpreted as encompassing various types of projection system, including refractive optics, reflective optics, and catadioptric systems, for example. The radiation system may also include components operating according to any of these design types for directing, shaping or controlling the projection beam of radiation, and such components may also be referred to below, collectively or singularly, as a "lens". Further, the lithographic apparatus may be of a type having two or more substrate tables (and/or two or more mask tables). In such "multiple stage" devices the additional tables may be used in parallel, or preparatory steps may be carried out on one or more tables while one or more other tables are being used for exposures. Twin stage lithographic apparatus are described, for example, in US 5,969,441 and WO 98/40791, incorporated herein by reference.

[0006] No material suitable for manufacturing refractive lenses usable with EUV radiation is known. Accordingly, a projection system for a lithographic apparatus making use of EUV radiation for the projection beam must be based on reflective optics, generally with multi-layer coated mirrors. Projection systems for EUV radiation have been proposed, for example in: "Design approach and comparison of projection cameras for EUV lithography", Lerner *et al*/Opt. Eng. 39(3) 792-802 March 2000; WO99/57596 (Braat); WO99/57606 (Braat), US 5,686,728 (Shafer) and US 5,815,310 (Williamson). These systems have various shortcomings, such as being far from telecentric or having very little working space, and a need exists for alternative systems. In a classification system described below, the Braat six-mirror systems fall into class 41(+) and the Williamson six-mirror design falls into class 45(-). The four-mirror systems described by Lerner *et al* fall into classes 9(+) and 10(-). The six- and eight-mirror systems described by Shafer fall into classes 41(+) and 165(+).

[0007] It is an object of the present invention to provide alternative and improved projection systems for EUV radiation and a methodology for designing such systems.

[0008] According to a first aspect of the present invention there is provided a lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate;
- a projection system for projecting the patterned beam onto a target portion of the substrate,

characterized in that:

said projection system has precisely four imaging mirrors in the optical path of the projection beam and has an incidence angle classification, C, of 2(-), 6(-), or 9(-), where:

$$C = \sum_{i=1}^4 a_i \cdot 2^{(4-i)} \left(\frac{M}{|M|} \right)$$

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,
 $a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,
 M is the magnification of the projection system, and
the index i numbers the mirrors from object to image.

[0009] According to a second aspect of the present invention there is provided a lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam

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according to a desired pattern;
a substrate table for holding a substrate;
a projection system for projecting the patterned beam onto a target portion of the substrate,

characterized in that:

said projection system has precisely six imaging mirrors in the optical path of the projection beam and has an incidence angle classification, C, of 5(+), 6(-), 9(+), 13(+), 18(-), 21(+), 22(-), 25(+), 29(+), 34(-), 37(+), 38(-), 42(-), or 54(-), where:

$$C = \sum_{i=1}^6 a_i \cdot 2^{(6-i)} \left(\frac{M}{|M|} \right)$$

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,
 $a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,
 M is the magnification of the projection system, and
the index i numbers the mirrors from object to image.

[0010] According to a third aspect of the present invention there is provided a lithographic projection apparatus comprising:

a radiation system for providing a projection beam of radiation;
a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
a substrate table for holding a substrate;
a projection system for projecting the patterned beam onto a target portion of the substrate,

characterized in that:

said projection system has precisely eight imaging mirrors in the optical path of the projection beam and has an incidence angle classification, C, of 2(+), 5(+), 9(+), 12(+), 13(+), 18(+), 18(-), 19(+), 20(+), 21(+), 22(+), 23(+), 25(+), 26(+), 34(-), 36(+), 37(+), 38(-), 45(+), 46(+), 49(+), 52(+), 53(+), 54(+), 54(-), 55(-), 58(-), 68(+), 69(+), 73(+), 74(+), 77(+), 82(+), 82(-), 85(+), 88(+), 89(+), 90(-), 92(+), 93(+), 97(+), 100(-), 101(+), 102(-), 104(+), 105(+), 106(+), 106(-), 107(+), 108(+), 109(+), 109(-), 110(+), 110(-), 111(+), 113(+), 116(+), 117(+), 118(+), 118(-), 120(+), 121(+), 122(-), 123(-), 132(+), 133(+), 134(-), 137(+), 138(+), 141(+), 145(+), 145(-), 146(+), 146(-), 147(+), 148(+), 148(-), 149(+), 150(+), 150(-), 151(+), 151(-), 152(-), 153(+), 154(+), 154(-), 155(+), 155(-), 156(+), 157(+), 159(+), 161(+), 162(-), 163(-), 164(+), 165(+), 166(+), 166(-), 167(+), 168(+), 169(+), 170(+), 170(-), 171(+), 172(+), 173(+), 174(+), 175(+), 176(+), 177(+), 178(-), 179(+), 180(+), 180(-), 181(+), 181(-), 182(+), 182(-), 183(+), 183(-), 184(+), 185(+), 185(-), 186(-), 187(+), 187(-), 188(-), 189(+), 196(+), 197(+), 201(+), 203(+), 205(+), 209(+), 214(-), 216(+), 217(+), 218(+), 218(-), 225(+), 228(+), 229(+), 230(+), 232(+), 233(+), 235(+), 236(+), 237(+), 238(-), 243(+), 246(+), 247(+), 248(+), 250(-), where:

$$C = \sum_{i=1}^8 a_i \cdot 2^{(8-i)} \left(\frac{M}{|M|} \right)$$

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,
 $a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,
 M is the magnification of the projection system, and
the index i numbers the mirrors from object to image.

[0011] An embodiment of the present invention may comprise a four-mirror projection system in class 6(-) with a numerical aperture of 0.15, a ring field between -22.8mm and -23.8mm on the image side, and a transverse magnification of -0.2 at a wavelength of 13nm. Such a system can have a minimum Strehl ratio of 0.972, a maximal wavefront error of 0.0266 waves and a maximal distortion of 12nm.

[0012] The present invention, in a fourth aspect also provides a device manufacturing method using a lithography apparatus comprising:

an illumination system constructed and arranged to supply a projection beam of radiation;
 a first object table constructed to hold a mask;
 a second object table constructed to hold a substrate; and
 a projection system constructed and arranged to image an irradiated portion of the mask onto target areas of the substrate; the method comprising the steps of:

providing a mask containing a pattern to said first object table;
 providing a substrate which is at least partially covered by a layer of radiation-sensitive material to said second object table;
 irradiating portions of the mask and imaging said irradiated portions of said mask onto said target areas of said substrate; characterized in that:

in the step of imaging, a projection system as defined in any one of the first, second and third aspects described above is used.

[0013] In a manufacturing process using a lithographic projection apparatus according to the invention a pattern in a mask is imaged onto a substrate which is at least partially covered by a layer of radiation-sensitive material (resist). Prior to this imaging step, the substrate may undergo various procedures, such as priming, resist coating and a soft bake. After exposure, the substrate may be subjected to other procedures, such as a post-exposure bake (PEB), development, a hard bake and measurement/inspection of the imaged features. This array of procedures is used as a basis to pattern an individual layer of a device, e.g. an IC. Such a patterned layer may then undergo various processes such as etching, ion-implantation (doping), metallization, oxidation, chemo-mechanical polishing, etc., all intended to finish off an individual layer. If several layers are required, then the whole procedure, or a variant thereof, will have to be repeated for each new layer. Eventually, an array of devices will be present on the substrate (wafer). These devices are then separated from one another by a technique such as dicing or sawing, whence the individual devices can be mounted on a carrier, connected to pins, etc. Further information regarding such processes can be obtained, for example, from the book "Microchip Fabrication: A Practical Guide to Semiconductor Processing", Third Edition, by Peter van Zant, McGraw Hill Publishing Co., 1997, ISBN 0-07-067250-4.

[0014] Although specific reference may be made in this text to the use of the apparatus according to the invention in the manufacture of ICs, it should be explicitly understood that such an apparatus has many other possible applications. For example, it may be employed in the manufacture of integrated optical systems, guidance and detection patterns for magnetic domain memories, liquid-crystal display panels, thin-film magnetic heads, etc. The skilled artisan will appreciate that, in the context of such alternative applications, any use of the terms "reticle", "wafer" or "die" in this text should be considered as being replaced by the more general terms "mask", "substrate" and "target portion", respectively.

[0015] In the present document, the terms "radiation" and "beam" are used to encompass all types of electromagnetic radiation, including ultraviolet radiation (e.g. with a wavelength of 365, 248, 193, 157 or 126 nm) and EUV (extreme ultra-violet radiation, e.g. having a wavelength in the range 5-20 nm), as well as particle beams, such as ion beams or electron beams.

[0016] The present invention and its attendant advantages will be described below with reference to exemplary embodiments and the accompanying schematic drawings, in which:

Fig. 1 depicts a lithographic projection apparatus according to a first embodiment of the invention;
 Fig. 2 is a diagram used in explaining the incidence angle classification system of the present invention;
 Fig. 3 is a diagram showing the thickness and curvature definitions used in the present invention;
 Fig. 4 is a diagram used in explaining how beam obstruction in a mirror design is determined;
 Fig. 5 is a diagram used in explaining how certain constraints are applied in designing mirror systems according to the invention;
 Figs. 6 to 19 are diagrams of mirror systems according to various embodiments of the invention.

[0017] In the various drawings, like parts are indicated by like references.

Embodiment 1

[0018] Figure 1 schematically depicts a lithographic projection apparatus according to a particular embodiment of

the invention. The apparatus comprises:

a radiation system Ex, IL, for supplying a projection beam PB of radiation (e.g. EUV radiation), which in this particular case also comprises a radiation source LA;

a first object table (mask table) MT provided with a mask holder for holding a mask MA (e.g. a reticle), and connected to first positioning means PM for accurately positioning the mask with respect to item PL;

a second object table (substrate table) WT provided with a substrate holder for holding a substrate W (e.g. a resist-coated silicon wafer), and connected to second positioning means PW for accurately positioning the substrate with respect to item PL;

a projection system ("lens") PL (e.g. a mirror group) for imaging an irradiated portion of the mask MA onto a target portion C (e.g. comprising one or more dies) of the substrate W. As here depicted, the apparatus is of a reflective type (i.e. has a reflective mask). However, in general, it may also be of a transmissive type, for example (with a transmissive mask). Alternatively, the apparatus may employ another kind of patterning means, such as a programmable mirror array of a type as referred to above.

[0019] The source LA (e.g. a discharge or laser-produced plasma source) produces a beam of radiation. This beam is fed into an illumination system (illuminator) IL, either directly or after having traversed conditioning means, such as a beam expander Ex, for example. The illuminator IL may comprise adjusting means AM for setting the outer and/or inner radial extent (commonly referred to as σ -outer and σ -inner, respectively) of the intensity distribution in the beam. In addition, it will generally comprise various other components, such as an integrator IN and a condenser CO. In this way, the beam PB impinging on the mask MA has a desired uniformity and intensity distribution in its cross-section.

[0020] It should be noted with regard to Figure 1 that the source LA may be within the housing of the lithographic projection apparatus (as is often the case when the source LA is a mercury lamp, for example), but that it may also be remote from the lithographic projection apparatus, the radiation beam which it produces being led into the apparatus (e.g. with the aid of suitable directing mirrors); this latter scenario is often the case when the source LA is an excimer laser. The current invention and Claims encompass both of these scenarios.

[0021] The beam PB subsequently intercepts the mask MA, which is held on a mask table MT. Having been selectively reflected by the mask MA, the beam PB passes through the lens PL, which focuses the beam PB onto a target portion C of the substrate W. With the aid of the second positioning means PW (and interferometric measuring means IF), the substrate table WT can be moved accurately, e.g. so as to position different target portions C in the path of the beam PB. Similarly, the first positioning means PM can be used to accurately position the mask MA with respect to the path of the beam PB, e.g. after mechanical retrieval of the mask MA from a mask library, or during a scan. In general, movement of the object tables MT, WT will be realized with the aid of a long-stroke module (course positioning) and a short-stroke module (fine positioning), which are not explicitly depicted in Figure 1. However, in the case of a wafer stepper (as opposed to a step-and-scan apparatus) the mask table MT may just be connected to a short stroke actuator, or may be fixed.

[0022] The depicted apparatus can be used in two different modes:

1. In step mode, the mask table MT is kept essentially stationary, and an entire mask image is projected in one go (i.e. a single "flash") onto a target portion C. The substrate table WT is then shifted in the x and/or y directions so that a different target portion C can be irradiated by the beam PB;

2. In scan mode, essentially the same scenario applies, except that a given target portion C is not exposed in a single "flash". Instead, the mask table MT is movable in a given direction (the so-called "scan direction", e.g. the y direction) with a speed v, so that the projection beam PB is caused to scan over a mask image; concurrently, the substrate table WT is simultaneously moved in the same or opposite direction at a speed $V = Mv$, in which M is the magnification of the lens PL (typically, $M = 1/4$ or $1/5$). In this manner, a relatively large target portion C can be exposed, without having to compromise on resolution.

Mirror System Classification

[0023] According to the present invention, a mirror system of n mirrors is classified by reference to the direction of the reflected beam compared to the incident beam at each mirror surface. Having defined the object height to be positive along a Y-axis and a suitable reference plane, e.g. the plane containing the optical axis Z of the projection system and the Y-axis (as shown in Figure 1), the chief ray CR at a mirror is defined as having a positive angle of incidence α , if the angle between the normal of the surface and the incident ray is counterclockwise (as shown in Figure 2) and a negative angle of incidence if the angle between the normal and the incident ray is clockwise. Further, one should view this reference plane along a positive X direction, the X, Y, Z directions making up a right-handed orthogonal coordinate system, as shown in Figure 1. The chief ray is defined as that ray emerging from the object point, which

goes through the center of the stop and therefore also through the center of the entrance and exit pupils, i.e. at a height equal to zero from the optical axis. (NB this assignment is arbitrary, the scheme can be implemented with either relative direction of reflection regarded as positive, provided that the assignment is consistent.) By assigning the binary digit "1" to a negative angle of incidence and "0" to a positive angle of incidence of the chief ray, a mirror system is assigned a binary number defined by the sequence of binary digits assigned to each mirror in the system in sequence along the optical path of the beam from object to source. For convenience, this binary number is expressed in decimal notation.

[0024] The various classes of the incidence angle classification system are further characterized by indicating the sign of the magnification of the system. Herein, this is indicated by the appropriate sign in parentheses after the class number, e.g. 6(-). The sign is obtained by dividing the magnification M by its absolute value $|M|$. A system has a positive magnification if the object and image are the same side of the optical axis and a negative magnification if they are opposite sides.

[0025] The decimal incidence angle classification, C , can thus be expressed as:

$$C = \sum_{i=1}^n a_i \cdot 2^{(n-i)} \left(\frac{M}{|M|} \right) \quad (1)$$

where:

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,

$a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,

M is the magnification of the projection system, and

index i numbers the mirrors of the system in series from object to source.

[0026] Figure 2 shows the four possible arrangements of incident chief rays CR and mirrors M. In A the incident chief ray is travelling left to right and has an angle of incidence $\alpha > 0$, so $a_i = 0$. In B the incident chief ray is travelling right to left and has an angle of incidence $\alpha < 0$, so $a_i = 1$. In C the incident chief ray is travelling right to left and has an angle of incidence $\alpha > 0$, so $a_i = 0$. In D the incident chief ray is travelling left to right with an angle of incidence $\alpha < 0$, so $a_i = 1$. Note that although convex mirrors are shown, the same assignments apply with concave or plane mirrors.

[0027] Whilst the incidence angle classification C does not wholly define a mirror system, the basic layout of a system is inherent in its incidence angle classification. By reference to whether the reflection at a given mirror is positive or negative, the orientation of that mirror and the position of the succeeding mirror, above or below the beam, can be determined. Thus a given classification number can be used by the designer of a mirror system to set out the system prior to optimization of that system, e.g. using commercially available ray tracing software such as CODE V(TM) by Optical Research Associates, Pasadena, California, USA. It should be noted that previous classifications of mirror systems based on whether the curvature, and hence power, of each mirror in the system is positive or negative, do not give any information as to the layout of a mirror system. It will also be noted that the incidence angle classification of a given mirror system can readily be determined from simple inspection of the beam path.

[0028] Using the above classification system and numerical simulations, the present inventors have determined that only certain classes contain mirror systems usable as the projection system in a lithographic projection system. For four-mirror systems, feasible projection systems exist in classes 2(-), 6(-), 9(+), 9(-) and 10(-). For six-mirror systems, feasible projection systems exist in classes 5(+), 6(-), 9(+), 13(+), 18(-), 21(+), 22(-), 25(+), 26(-), 29(+), 34(-), 37(+), 38(-), 41(+), 42(-), 45(+) and 54(-). For eight-mirror systems, feasible projection systems exist in class 2(+), 5(+), 9(+), 12(+), 13(+), 18(+), 18(-), 19(+), 20(+), 21(+), 22(+), 23(+), 25(+), 26(+), 34(-), 36(+), 37(+), 38(-), 45(+), 46(+), 49(+), 52(+), 53(+), 54(+), 54(-), 55(-), 58(-), 68(+), 69(+), 73(+), 74(+), 77(+), 82(+), 82(-), 85(+), 88(+), 89(+), 90(-), 92(+), 93(+), 97(+), 100(-), 101(+), 102(-), 104(+), 105(+), 106(+), 106(-), 107(+), 108(+), 109(+), 109(-), 110(+), 110(-), 111(+), 113(+), 116(+), 117(+), 118(+), 118(-), 120(+), 121(+), 122(-), 123(-), 132(+), 133(+), 134(-), 137(+), 138(+), 141(+), 145(+), 145(-), 146(+), 146(-), 147(+), 148(+), 148(-), 149(+), 150(+), 150(-), 151(+), 151(-), 152(-), 153(+), 154(+), 154(-), 155(+), 155(-), 156(+), 157(+), 159(+), 161(+), 162(-), 163(-), 164(+), 165(+), 166(+), 166(-), 167(+), 168(+), 169(+), 170(+), 170(-), 171(+), 172(+), 173(+), 174(+), 175(+), 176(+), 177(+), 178(-), 179(+), 180(+), 180(-), 181(+), 181(-), 182(+), 182(-), 183(+), 183(-), 184(+), 185(+), 185(-), 186(-), 187(+), 187(-), 188(-), 189(+), 196(+), 197(+), 201(+), 203(+), 205(+), 209(+), 214(-), 216(+), 217(+), 218(+), 218(-), 225(+), 228(+), 229(+), 230(+), 232(+), 233(+), 235(+), 236(+), 237(+), 238(-), 243(+), 246(+), 247(+), 248(+), 250(-).

Design Methodology

[0029] As mentioned above, a given class defines an outline layout for a mirror system for which a functional pro-

jection system can be designed. A methodology according to the present invention for such a design process is described below.

[0030] In the design process according to the invention, the mirrors in a system are defined by "thicknesses" and curvatures, defined as shown in Figure 3. (NB the term "thickness" is used by analogy to refractive systems which are conventionally defined in terms of surface curvatures, thicknesses between surfaces and the refractive indices of the media between surfaces.) Thus, thickness d_0 is the distance between the object, the mask MA in the present case of a projection system in a lithographic apparatus, and the intersection of the (imaging extended) first mirror M_1 with the optical axis OA. The distance between the intersections of the (imaging extended) first mirror M_1 and the (imaging extended) second mirror M_2 with the optical axis OA is d_1 . Note that since the second mirror is situated between the first mirror M_1 and the object (mask MA), thickness d_1 is negative. In general, thickness d_i is the distance between the intersections of mirror M_i and mirror M_{i+1} with the optical axis OA. For an n-mirror system, the thickness d_n is the distance between the last mirror M_n and the image plane, where the substrate W is positioned in a lithographic projection apparatus. In specific embodiments described below, an additional thickness d_{n+1} is given, this represents the distance between the position of the image calculated using a first order approximation and using a real ray tracing algorithm.

[0031] In a first step the design method identifies conceivable systems under a number of constraints by using a paraxial approach described below. Those systems should not present obscuration, as is also described further below. The paraxial approach and the constraints yield a limited number of variables that are sampled to identify solutions. In a further step those solutions are checked using a real ray tracing method, referred to above, in which the paraxial assumptions are not present and in which also multilayer coatings of the reflectors may be modelled.

Paraxial Approach

[0032] The present inventors have developed an approach to designing mirror systems which starts with a paraxial approximation of a mirror system using matrix formalism. In a paraxial approximation the sine of an angle is approximated as the angle, i.e. $\sin \alpha = \alpha$, and are the mirrors considered as being flat, while the actual curvature of a mirror is considered only to affect the angle of an incident ray, not its point of intersection with the supposedly 'flat' surface.

[0033] In a matrix formalism, such as described in "Introduction to Optics" by Frank & Leno Pedrotti, Prentice Hall 1993; ISBN: 0135015456, incorporated herein by reference, the description of an optical system consist of an accumulation of translation and reflection (and/or refraction in a catadioptric or refractive system) matrices M_{trans} , M_{refl} which are defined as follows:

$$M_{trans} = \begin{bmatrix} 1 & d_i \\ 0 & 1 \end{bmatrix} \quad (2)$$

$$M_{refl} = \begin{bmatrix} 1 & 0 \\ -2c_i & -1 \end{bmatrix} \quad (3)$$

where d_i is the distance to the next surface and c_i the curvature of the surface, which is positive if the center of the sphere is on the right side of the surface. The path of a ray is given by a vector made of a height (distance from the optical axis) and an angle: [height, angle]. The multiplication of the vector with one or more matrices gives the ray after the corresponding translations or reflections.

[0034] The system matrix is the multiplication of all the matrices in the system. The first matrix is the reflection matrix of the first surface, the penultimate matrix is the translation matrix of the thickness preceding the last reflective surface and the last matrix is the reflection matrix of the last reflective surface. The effective focal length, the back focal length, the front focal length and the paraxial image distance can be derived from the system matrix as follows.

[0035] If the system matrix is defined as:

$$M_{system} = \begin{bmatrix} a & b \\ c & d \end{bmatrix} \quad (4)$$

then the effective focal length is given by:

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$$efl = -\frac{1}{c} \quad (5)$$

the back focal length is given by:

$$bfl = -\frac{a}{c} \quad (6)$$

the front focal length is given by:

$$ffl = \frac{d}{c} \quad (7)$$

and the paraxial image distance, i.e. the distance between the last reflective surface and the image plane, is given by:

$$d_n = \frac{a \cdot d_0 + b}{c \cdot d_0 + d} \quad (8)$$

where

$$d_0 = \frac{ad - cb - magn \cdot d}{magn \cdot c}$$

and *magn* is the magnification of the system.

[0036] The system matrix for the first part of the system, from the object plane to the stop (pupil) can be represented as:

$$M_{1st} = \begin{bmatrix} a_{1st} & b_{1st} \\ c_{1st} & d_{1st} \end{bmatrix} \quad (9)$$

so that the distance, L_{enpup} , to the entrance pupil is given by:

$$\begin{bmatrix} a_{1st} & b_{1st} \\ c_{1st} & d_{1st} \end{bmatrix} \begin{bmatrix} 1 & L_{enpup} \\ 0 & 1 \end{bmatrix} \begin{bmatrix} 0 \\ A_{enpup} \end{bmatrix} = \begin{bmatrix} (a_{1st} \cdot L_{enpup} + b_{1st}) \cdot A_{enpup} \\ (c_{1st} \cdot L_{enpup} + d_{1st}) \cdot A_{enpup} \end{bmatrix} = \begin{bmatrix} 0 \\ A_{stop} \end{bmatrix} \quad (10)$$

[0037] The second part of the system, from stop to image surface can be represented as:

$$M_{2nd} = \begin{bmatrix} a_{2nd} & b_{2nd} \\ c_{2nd} & d_{2nd} \end{bmatrix} \quad (11)$$

so that the distance, L_{expup} , to the exit pupil is given by:

$$\begin{bmatrix} 1 & L_{expup} \\ 0 & 1 \end{bmatrix} \begin{bmatrix} a_{2nd} & b_{2nd} \\ c_{2nd} & d_{2nd} \end{bmatrix} \begin{bmatrix} 0 \\ A_{stop} \end{bmatrix} = \begin{bmatrix} (b_{2nd} + L_{expup} \cdot d_{2nd}) \cdot A_{stop} \\ D_{2nd} \cdot A_{stop} \end{bmatrix} = \begin{bmatrix} 0 \\ A_{expup} \end{bmatrix} \quad (12)$$

The distances to the entrance and exit pupils, if $A_{enpup} \neq 0$, are then given by:

$$L_{\text{enpup}} = \frac{b_{1st}}{a_{1st}} \text{ and } L_{\text{expup}} = -\frac{b_{2nd}}{d_{2nd}} \quad (13)$$

5 Constraints

[0038] Given the above, various constraints that must be applied to the system can be used to determine equations for the curvatures and thicknesses of certain surfaces of the system as functions of the constraints and other curvatures and thicknesses. Some example constraints G1 to G4 are shown in Figure 5.

[0039] A first constraint G1 is minimum deviation from telecentricity on the object side that still enables obscuration-free illumination of the object, which may determine the curvature of the first surface or the thickness between mirrors 1 and 2. Another constraint G3, is perfect telecentricity on the image side, which may determine the curvature of the last surface or the thickness between the final and penultimate mirrors. This telecentricity requirement is equivalent to the requirement that the exit pupil is at infinity. The requirement that the object and the image are conjugated and have a prescribed value of the transverse magnification fixes the values of the object (G2) and image (G4) distances.

[0040] The object distance G2, the first thickness, can be solved as a function of the desired magnification of the system: the paraxial image distance is inserted in the thickness of the surface immediately preceding the image plane and the object distance is modified to satisfy:

$$M = \frac{\text{Image Height}}{\text{Object Height}} \quad (14)$$

[0041] In current lithography apparatus, M is usually set as ± 0.20 or ± 0.25 , i.e. reduction by a factor of 5 or 4 respectively.

[0042] A minimum deviation from telecentricity at the object side is an important requirement in lithography. The reflective object (mask MA) is illuminated with a beam coming from the radiation system. The chief ray angle at the object must be such that the incident illuminating beam does not interfere with the beam reflected from the object and going into the projection system. The angle of the chief ray together with the numerical aperture on the object side should be almost zero and the angles of all rays must be smaller or larger than zero, to fulfil these two requirements. For telecentricity on the image side, the angle of the chief ray relative to the optical axis has to be zero. The size of the last mirror increases quickly as a function of the distance between the image and the last mirror, due to the relatively large numerical aperture.

[0043] A system with zero or an even number of intermediate images has a negative magnification. To have an overall system with a positive magnification the number of intermediate images has to be odd.

[0044] The working distance at the object side is the minimum distance between the object plane and the surface closest to the object, most of the time the second mirror. On the image side the working distance is the minimum distance between the image plane and the plane closest to the image, most often the penultimate mirror. The working distances provide room for mirror supports and for mechanical movements of the object and the image and must not be too small.

[0045] An example of applying the above constraints in a six-mirror system is described below. This may be carried out in practice using software such as Maple (TM) produced by Waterloo Maple Inc. 57 Erb Street W. Waterloo, Ontario Canada N2L 6C2.

[0046] First is a derivation of the formulas used for a six-mirror system, but the formulas are also valid for other numbers of mirrors, using the paraxial approach. In the matrix notation a ray is defined by the vector: [height, angle in radians]. After a distance d_i the ray [y,a] will be:

$$\begin{bmatrix} y + d_i a \\ a \end{bmatrix} \quad (15)$$

using the matrix given in equation (2).

After a mirror with curvature c_i the ray [y,a] will have the same height but a different angle:

$$\begin{bmatrix} y \\ -2cy - a \end{bmatrix} \quad (16)$$

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using the matrix given in equation (3).

To derive formulas used later on, firstly the distance between mirror 5 and 6 is solved by requiring telecentricity in the image of the ray going through the optical axis in the stop surface. The following matrix A is from the stop surface to after the 5th mirror, as we don't now where we will locate the stop surface we take an unknown 2 by 2 matrix:

$$A := \begin{bmatrix} a & b \\ c & d \end{bmatrix} \quad (17)$$

From the 5th mirror we travel a distance la to the 6th mirror, la is the variable to solve now.

$$L6 := \begin{bmatrix} 1 & la \\ 0 & 1 \end{bmatrix} \quad (18)$$

Matrix MC is of the 6th mirror surface:

$$MC := \begin{bmatrix} 1 & 0 \\ -2 \, c6 & -1 \end{bmatrix} \quad (19)$$

The ray going through the center of the stop with an arbitrary angle ap is:

$$Y := \begin{bmatrix} 0 \\ ap \end{bmatrix} \quad (20)$$

That ray after the 6th mirror will be:

$$Y_image := \begin{bmatrix} (b + la \, d) \, ap \\ (-2 \, c6 \, b + (-2 \, c6 \, la - 1) \, d) \, ap \end{bmatrix} \quad (21)$$

in which the angle is equal to zero since telecentricity is required and the solution opl for the distance la between mirror five and six is now

$$opl := \frac{1}{-2} \frac{2 \, c6 \, b + d}{c6 \, d} \quad (22)$$

The matrix from the stop surface to after the 6th mirror is now:

$$B := \begin{bmatrix} \frac{1}{2} \frac{2 \, c6 \, a \, d - 2 \, c6 \, b \, c - c \, d}{c6 \, d} & -\frac{1}{2} \frac{d}{c6} \\ -2 \frac{c6 \, (d \, a - b \, c)}{d} & 0 \end{bmatrix} \quad (23)$$

The next solve is the distance d between the object and the first mirror and the solve ya for the angle of the chief ray (going through the center of the stop) between the object and the first mirror.

The ray Ya in the object point yob with the desired angle ya is given by the vector:

$$Y_a := \begin{bmatrix} y_{ob} \\ y_a \end{bmatrix} \quad (24)$$

and the distance l between the object and the first mirror surface by the matrix:

$$L := \begin{bmatrix} 1 & l \\ 0 & 1 \end{bmatrix} \quad (25)$$

The first mirror surface is given by:

$$MC := \begin{bmatrix} 1 & 0 \\ -2cl & -1 \end{bmatrix} \quad (26)$$

The distance m between the first mirror and the second mirror is given by:

$$M := \begin{bmatrix} 1 & m \\ 0 & 1 \end{bmatrix} \quad (27)$$

The unknown matrix from the second mirror surface to the stop position is defined as

$$A := \begin{bmatrix} e & f \\ g & h \end{bmatrix} \quad (28)$$

The chief ray in the stop surface is now:

$$Y_{stop} := \begin{bmatrix} (e - 2(e m + f) c l) y_{ob} + ((e - 2(e m + f) c l) l - e m - f) y_a \\ (g - 2(g m + h) c l) y_{ob} + ((g - 2(g m + h) c l) l - g m - h) y_a \end{bmatrix} \quad (29)$$

and in the image the chief ray is:

$Y_{image} :=$

$$\begin{aligned}
 & \left[\left(\frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) e}{\sigma d} - \frac{1}{2} \frac{d g}{\sigma} - 2 \left(\left(\frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) e}{\sigma d} - \frac{1}{2} \frac{d g}{\sigma} \right) m + \frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) f}{\sigma d} - \frac{1}{2} \frac{d b}{\sigma} \right) d \right) yob \right. \\
 & + \left. \left(\left(\frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) e}{\sigma d} - \frac{1}{2} \frac{d g}{\sigma} - 2 \left(\left(\frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) e}{\sigma d} - \frac{1}{2} \frac{d g}{\sigma} \right) m + \frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) f}{\sigma d} - \frac{1}{2} \frac{d b}{\sigma} \right) d \right) l \right. \right. \\
 & \left. \left. - \left(\frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) e}{\sigma d} - \frac{1}{2} \frac{d g}{\sigma} \right) m - \frac{1}{2} \frac{(2 \sigma a d - 2 \sigma b c - c d) f}{\sigma d} + \frac{1}{2} \frac{d b}{\sigma} \right) y \right] \\
 & \left[\left(-2 \frac{\sigma (d a - b c) e}{d} - 2 \left(-2 \frac{\sigma (d a - b c) e m}{d} - 2 \frac{\sigma (d a - b c) f}{d} \right) d \right) yob \right. \\
 & + \left. \left(\left(-2 \frac{\sigma (d a - b c) e}{d} - 2 \left(-2 \frac{\sigma (d a - b c) e m}{d} - 2 \frac{\sigma (d a - b c) f}{d} \right) d \right) l + 2 \frac{\sigma (d a - b c) e m}{d} + 2 \frac{\sigma (d a - b c) f}{d} \right) y \right]
 \end{aligned} \tag{30}$$

The height of the chief ray in the image is by definition $magn \cdot height$ in the object surface (yob), we solve l from equation (30) to impose this reduction to the system giving:

$$\begin{aligned}
 Y_{image_l} &:= (2 yob e c6 a d - 2 yob e c6 b c - yob e c d - yob d^2 g - 4 yob c1 m e c6 a d \\
 & + 4 yob c1 m e c6 b c + 2 yob c1 m e c d + 2 yob c1 m d^2 g - 4 yob c1 f c6 a d + 4 yob c1 f c6 b c \\
 & + 2 yob c1 f c d + 2 yob c1 d^2 h - 2 ya m e c6 a d + 2 ya m e c6 b c + ya m e c d + ya m d^2 g \\
 & - 2 ya f c6 a d + 2 ya f c6 b c + ya f c d + ya d^2 h - 2 magn yob c6 d) \\
 & l ((2 e c6 a d - 2 e c6 b c - e c d - d^2 g - 4 c1 m e c6 a d + 4 c1 m e c6 b c + 2 c1 m e c d \\
 & + 2 c1 m d^2 g - 4 c1 f c6 a d + 4 c1 f c6 b c + 2 c1 f c d + 2 c1 d^2 h) ya)
 \end{aligned} \tag{31}$$

and we force the height of the chief ray to be zero in the stop surface in equation (29), as it should be by definition to solve the distance m :

$$Y_{stop_m} := - \frac{yob e + 2 yob f c l + ya l e + 2 ya f c l + ya f}{e(2 yob c l + 2 ya c l + ya)} \tag{32}$$

The solution for the distance m between the first and the second mirror now becomes:

$$Y_{stop_m} := \frac{1}{4} \frac{4 f c l magn yob c6 + 2 e magn yob c6 + e ya d h + ya f d g}{e c l magn yob c6} \tag{33}$$

The solution for the distance l between the object and the first mirror now is:

$$Y_{image_l} := - \frac{1}{2} \frac{ya f d g + 2 d yob c l f g + e ya d h + 2 d e yob c l h + 2 e magn yob c6}{ya(f g e h) c l d} \tag{34}$$

We substitute the just derived expressions in the matrices L and M of equations (25) and (27).

$$M := \begin{bmatrix} 1 & \frac{1}{4} \frac{-4 f c l \text{ magn } y o b c \delta + 2 e \text{ magn } y o b c \delta - e y a d h + y a f d g}{e c l \text{ magn } y o b c \delta} \\ 0 & 1 \end{bmatrix} \quad (35)$$

$$L := \begin{bmatrix} 1 & -\frac{1}{2} \frac{y a f d g + 2 d y o b c l f g - e y a d h - 2 d e y o b c l h + 2 e \text{ magn } y o b c \delta}{y a (f g - e h) c l d} \\ 0 & 1 \end{bmatrix} \quad (36)$$

And as a check we calculate the chief ray after the 6th surface with the new expressions. We see that the angle is always zero and that the height is the object height multiplied with magnification.

$$Y_image := \begin{bmatrix} \text{magn } y o b \\ 0 \end{bmatrix} \quad (37)$$

The final solve is the distance n between the last mirror surface and the image surface. In the image surface all rays from the same object point come together in a point with a height = magnification * object height.

[0047] First we define a ray Yb from the object point yob and an arbitrary angle $y b$.

$$Yb := \begin{bmatrix} y o b \\ y b \end{bmatrix} \quad (38)$$

$$N := \begin{bmatrix} 1 & n \\ 0 & 1 \end{bmatrix} \quad (39)$$

In the image this ray Yb will become:

$Y_image :=$

$$\begin{aligned} & \left[-\frac{1}{4} (-f g^2 d^2 y a^2 + g d^2 e y a^2 h - g y b d^2 e y a h + 2 y b e^2 a d y a h - 4 y b \text{ magn}^2 y o b a^2 e \right. \\ & - 4 y b e^2 n a^2 d a y a h + 4 y b e^2 n a^2 b c y a h + e^2 c d y a^2 h - 4 e^2 n a^2 b c y a^2 h \\ & + 4 e^2 n a^2 d a y a^2 h + 2 e^2 a b c y a^2 h - 2 e^2 a d y a^2 b - 2 y b e^2 a b c y a h \\ & - 4 y a d c l \text{ magn } y o b a e h + 4 y b d c l \text{ magn } y o b a e h - y b e^2 c d y a h + f g^2 y b d^2 y a + f g y b e c d y a \\ & - 4 f g e n a^2 d a y a^2 + 2 f g y b e a b c y a - 2 f g e a b c y a^2 - 4 f g y b d c l \text{ magn } y o b a \\ & + 2 f g e a d y a^2 + 4 f g y a d c l \text{ magn } y o b a + 4 f g e n a^2 b c y a^2 - f g e c d y a^2 \\ & \left. + 4 f g y b e n a^2 d a y a - 4 f g y b e n a^2 b c y a - 2 f g y b e a d y a) / (y a \text{ magn}^2 e a^2) \right] \\ & \left[-\frac{(-y a + y b) (f g - e h) (d a - b c)}{\text{magn}} \right] \end{aligned} \quad (40)$$

The expression for the image distance n is, given that the image height is equal to $\text{magn} \cdot y o b$:

$$\begin{aligned}
Y_{\text{image}_n^o} := & \frac{1}{4}(-d^2 g e y a h + 2 e^2 c_6 a d y a h - 4 \text{ magn}^2 y o b c_6^2 e + 2 e c_6 b c y a f g \\
& - 4 d g f c_1 \text{ magn} y o b c_6 - 2 e^2 c_6 b c y a h + e c d y a f g + 4 d h c_6 e c_1 \text{ magn} y o b - e^2 c d y a h \\
& + d^2 g^2 y a f - 2 e c_6 a d y a f g) / ((-e d a h + e b c h + f g d a - f g b c) e c_6^2 y a)
\end{aligned} \quad (41)$$

6-mirror system, stop on mirror 2

[0048] Now we use these derivations in the first part: solving the variables of a six-mirror system with the stop position on mirror two, defining thicknesses as $d := [d_0, d_1, d_2, d_3, d_4, d_5, d_6]$ and the curvatures as $c := [c_1, c_2, c_3, c_4, c_5, c_6]$. The stop (pupil) position is on the second surface.

[0049] A limitation on the Petzval sum (i.e. the sum of curvatures in the system, curvatures of odd surfaces being subtracted from curvatures of even surfaces, or vice versa), e.g. to be zero, can be introduced and used to solve the curvature of the stop surface. However, a zero Petzval sum is not essential and a non-zero value can be accommodated.

[0050] Now we define all the matrices in the system, the reflectance (even subscripts) and translation (odd subscripts) matrices, from the object to the image.

$$\begin{aligned}
M_1 &:= \begin{bmatrix} 1 & d_0 \\ 0 & 1 \end{bmatrix} & M_2 &:= \begin{bmatrix} 1 & 0 \\ -2 c_1 & -1 \end{bmatrix} \\
M_3 &:= \begin{bmatrix} 1 & d_1 \\ 0 & 1 \end{bmatrix} & M_4 &:= \begin{bmatrix} 1 & 0 \\ -2 c_2 & -1 \end{bmatrix} \\
M_5 &:= \begin{bmatrix} 1 & d_2 \\ 0 & 1 \end{bmatrix} & M_6 &:= \begin{bmatrix} 1 & 0 \\ -2 c_3 & -1 \end{bmatrix} \\
M_7 &:= \begin{bmatrix} 1 & d_3 \\ 0 & 1 \end{bmatrix} & M_8 &:= \begin{bmatrix} 1 & 0 \\ -2 c_4 & -1 \end{bmatrix} \\
M_9 &:= \begin{bmatrix} 1 & d_4 \\ 0 & 1 \end{bmatrix} & M_{10} &:= \begin{bmatrix} 1 & 0 \\ -2 c_5 & -1 \end{bmatrix} \\
M_{11} &:= \begin{bmatrix} 1 & d_5 \\ 0 & 1 \end{bmatrix} & M_{12} &:= \begin{bmatrix} 1 & 0 \\ -2 c_6 & -1 \end{bmatrix} \\
M_{13} &:= \begin{bmatrix} 1 & d_6 \\ 0 & 1 \end{bmatrix}
\end{aligned} \quad (42)$$

[0051] The first solve is the exit pupil in infinity or telecentricity in the image. The angle of the ray going through the optical axis in the stop surface should be zero in the image. The matrix from the stop surface to the fifth mirror generated by multiplication of the appropriate M matrices derived just above, is given by:

$$\begin{aligned}
& [1_2 d_3 c_3 + d_4 (-2 c_4 (1_2 d_3 c_3) + 2 c_3), d_2 + d_3 (-2 c_3 d_2 - 1) + d_4 (-2 c_4 (d_2 + d_3 (-2 c_3 d_2 - 1)) + 2 c_3 d_2 + 1)] \\
& [-2 c_5 (1_2 d_3 c_3 + d_4 (-2 c_4 (1_2 d_3 c_3) + 2 c_3)) + 2 c_4 (1_2 d_3 c_3) - 2 c_3, \\
& -2 c_5 (d_2 + d_3 (-2 c_3 d_2 - 1)) + d_4 (-2 c_4 (d_2 + d_3 (-2 c_3 d_2 - 1)) + 2 c_3 d_2 + 1) + 2 c_4 (d_2 + d_3 (-2 c_3 d_2 - 1)) - 2 c_3 d_2 - 1]
\end{aligned} \quad (43)$$

The matrix from the second mirror surface to the stop surface is given by:

$$\begin{bmatrix} 1 & 0 \\ -2c2 & -1 \end{bmatrix}$$

(44)

So as we derived the distance between mirror 5 and 6, we solve this new found value in the appropriate matrix and the vector of distances.

$$d5 := \frac{1}{2} (2 c6 d2 - 4 c6 d3 c3 d2 - 2 c6 d3 - 4 c6 d4 c4 d2 + 8 c6 d4 c4 d3 c3 d2 + 4 c6 d4 c4 d3 + 4 c6 d4 c3 d2 + 2 c6 d4 - 2 c5 d2 + 4 c5 d3 c3 d2 + 2 c5 d3 + 4 c5 d4 c4 d2 - 8 c5 d4 c4 d3 c3 d2 - 4 c5 d4 c4 d3 - 4 c5 d4 c3 d2 - 2 c5 d4 + 2 c4 d2 - 4 c4 d3 c3 d2 - 2 c4 d3 - 2 c3 d2 - 1) / (c6 (2 c5 d2 - 4 c5 d3 c3 d2 - 2 c5 d3 - 4 c5 d4 c4 d2 + 8 c5 d4 c4 d3 c3 d2 + 4 c5 d4 c4 d3 + 4 c5 d4 c3 d2 + 2 c5 d4 - 2 c4 d2 + 4 c4 d3 c3 d2 + 2 c4 d3 + 2 c3 d2 + 1)) \quad (45)$$

The distance between mirror one and two is derived as:

$$d1 := -\frac{1}{4} \frac{-2 \text{ magn yob } c6 - \text{angle} (-2 c5 (d2 + d3 (-2 c3 d2 - 1)) + d4 (-2 c4 (d2 + d3 (-2 c3 d2 - 1)) + 2 c3 d2 + 1)) + 2 c4 (d2 + d3 (-2 c3 d2 - 1)) - 2 c3 d2 - 1}{d1 \text{ magn yob } c6} \quad (46)$$

and the distance between the object and the first mirror is:

$$d0 := \frac{1}{2} (-\text{angle} (-2 c5 (d2 + d3 (-2 c3 d2 - 1)) + d4 (-2 c4 (d2 + d3 (-2 c3 d2 - 1)) + 2 c3 d2 + 1)) + 2 c4 (d2 + d3 (-2 c3 d2 - 1)) - 2 c3 d2 - 1) - 2 c1 \text{ yob} (-2 c5 (d2 + d3 (-2 c3 d2 - 1)) + d4 (-2 c4 (d2 + d3 (-2 c3 d2 - 1)) + 2 c3 d2 + 1)) + 2 c4 (d2 + d3 (-2 c3 d2 - 1)) - 2 c3 d2 - 1 - 2 \text{ magn yob } c6) / (\text{angle } c1 (-2 c5 (d2 + d3 (-2 c3 d2 - 1)) + d4 (-2 c4 (d2 + d3 (-2 c3 d2 - 1)) + 2 c3 d2 + 1)) + 2 c4 (d2 + d3 (-2 c3 d2 - 1)) - 2 c3 d2 - 1) \quad (47)$$

The distance between mirror six and the image surface is:

$$d6 := -\frac{1}{4} (2 \text{ angle} (1 - 2 d3 c3 + d4 (-2 c4 (1 - 2 d3 c3) + 2 c3)) c6 (-2 c5 (d2 + d3 (-2 c3 d2 - 1)) + d4 (-2 c4 (d2 + d3 (-2 c3 d2 - 1)) + 2 c3 d2 + 1)) + 2 c4 (d2 + d3 (-2 c3 d2 - 1)) - 2 c3 d2 - 1 - \text{angle} (-2 c5 (1 - 2 d3 c3 + d4 (-2 c4 (1 - 2 d3 c3) + 2 c3)) + 2 c4 (1 - 2 d3 c3) - 2 c3) c6 (d2 + d3 (-2 c3 d2 - 1)) + d4 (d2 + d3 (d2 + d3 (-2 c3 d2 - 1)) + 2 c3 d2 + 1)) - \text{angle}$$

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$$\begin{aligned}
 & _2 c5 (1_2 d3 c3 + d4 (_2 c4 (1_2 d3 c3) + 2 c3)) + 2 c4 (1_2 d3 c3) _2 c3 (\\
 & _2 c5 (d2 + d3 (_2 c3 d2 - 1) + d4 (_2 c4 (d2 + d3 (_2 c3 d2 - 1)) + 2 c3 d2 + 1)) \\
 & + 2 c4 (d2 + d3 (_2 c3 d2 - 1)) _2 c3 d2 - 1 + 2 \text{ angle} (\\
 & _2 c5 (d2 + d3 (_2 c3 d2 - 1) + d4 (_2 c4 (d2 + d3 (_2 c3 d2 - 1)) + 2 c3 d2 + 1)) \\
 & + 2 c4 (d2 + d3 (_2 c3 d2 - 1)) _2 c3 d2 - 1)^2 c2 + 4 c1 (\\
 & _2 c5 (d2 + d3 (_2 c3 d2 - 1) + d4 (_2 c4 (d2 + d3 (_2 c3 d2 - 1)) + 2 c3 d2 + 1)) \\
 & + 2 c4 (d2 + d3 (_2 c3 d2 - 1)) _2 c3 d2 - 1 \text{ magn yob } c6 + 4 \text{ magn}^2 \text{ yob } c6^2) / ((\\
 & (_2 c5 (1_2 d3 c3 + d4 (_2 c4 (1_2 d3 c3) + 2 c3)) + 2 c4 (1_2 d3 c3) _2 c3) \\
 & (d2 + d3 (_2 c3 d2 - 1) + d4 (_2 c4 (d2 + d3 (_2 c3 d2 - 1)) + 2 c3 d2 + 1)) _2 c3 d2 - 1) (\\
 & _2 c5 (d2 + d3 (_2 c3 d2 - 1) + d4 (_2 c4 (d2 + d3 (_2 c3 d2 - 1)) + 2 c3 d2 + 1)) \\
 & + 2 c4 (d2 + d3 (_2 c3 d2 - 1)) _2 c3 d2 - 1) (1_2 d3 c3 + d4 (_2 c4 (1_2 d3 c3) + 2 c3))) \\
 & c6^2 \text{ angle} \tag{48}
 \end{aligned}$$

The variable *angle* is identical to *ya* introduced in equation (24) above.

6-mirror system, stop on mirror 3

[0052] The original derivations can similarly be used to solve the variables of a six-mirror system with the stop position on mirror three, as will now be shown.

[0053] The first solve is pupil in infinity or telecentricity in the image. The angle of the ray going through the optical axis in the stop surface should be zero in the image. The matrix from the stop surface to the fifth mirror generated by multiplication of the appropriate M matrices derived just above, is given by:

$$\begin{bmatrix} 1_2 d4 c4 & d3 + d4 (_2 c4 d3 - 1) \\ _2 c5 (1_2 d4 c4) + 2 c4 & _2 c5 (d3 + d4 (_2 c4 d3 - 1)) + 2 c4 d3 + 1 \end{bmatrix} \tag{50}$$

The matrix from the second mirror surface to the stop surface is given by:

$$\begin{bmatrix} 1_2 d2 c2 & _d2 \\ _2 c3 (1_2 d2 c2) + 2 c2 & 2 c3 d2 + 1 \end{bmatrix} \tag{51}$$

So, as derived above, the distance between mirror 5 and 6 is, solved this new found value in the appropriate matrix and the vector of distances:

$$d5 := - \frac{1_2 c6 d3 - 4 c6 d4 c4 d3 - 2 c6 d4 - 2 c5 d3 + 4 c5 d4 c4 d3 + 2 c5 d4 + 2 c4 d3 + 1}{c6 (-2 c5 d3 + 4 c5 d4 c4 d3 + 2 c5 d4 + 2 c4 d3 + 1)} \tag{51}$$

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The distance between mirror one and two was:

$$\begin{aligned}
 d1 = & -\frac{1}{4} (-4 d2 c1 \text{ magn yob } c6 - 2 (1 - 2 d2 c2) \text{ magn yob } c6 \\
 & + (1 - 2 d2 c2) \text{ angle } (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (2 c3 d2 + 1) \\
 & + \text{angle } d2 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (-2 c3 (1 - 2 d2 c2) + 2 c2)) / \\
 & ((1 - 2 d2 c2) \text{ of magn yob } c6)
 \end{aligned} \tag{52}$$

And the distance between the object and the first mirror:

$$\begin{aligned}
 d0 : = & -\frac{1}{2} ((1 - 2 d2 c2) \text{ angle } (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (2 c3 d2 + 1) \\
 & + \text{angle } d2 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (-2 c3 (1 - 2 d2 c2) + 2 c2) \\
 & + 2 c1 \text{ yob } d2 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (-2 c3 (1 - 2 d2 c2) + 2 c2) \\
 & + 2 c1 \text{ yob } (1 - 2 d2 c2) (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (2 c3 d2 + 1) \\
 & - 2 (1 - 2 d2 c2) \text{ magn yob } c6) / (\text{angle } ((-2 c3 (1 - 2 d2 c2) + 2 c2) d2 \\
 & + (2 c3 d2 + 1) (1 - 2 d2 c2)) c1 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1))
 \end{aligned} \tag{53}$$

And the distance between mirror six and the image surface:

$$\begin{aligned}
 d6 := & -\frac{1}{4} (-2 \\
 & \text{angle } (1 - 2 d2 c2)^2 (1 - 2 d4 c4) c6 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (2 c3 d2 + 1) \\
 & - 2 \text{angle } (1 - 2 d2 c2) (1 - 2 d4 c4) c6 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) d2 \\
 & (-2 c3 (1 - 2 d2 c2) + 2 c2) \\
 & + 2 \text{angle } (1 - 2 d2 c2)^2 (-2 c5 (1 - 2 d4 c4) + 2 c4) c6 (d3 + d4 (-2 c4 d3 - 1)) (2 c3 d2 + 1) + \\
 & 2 \text{angle } (1 - 2 d2 c2) (-2 c5 (1 - 2 d4 c4) + 2 c4) c6 (d3 + d4 (-2 c4 d3 - 1)) d2 \\
 & (-2 c3 (1 - 2 d2 c2) + 2 c2) + \text{angle } (1 - 2 d2 c2)^2 (-2 c5 (1 - 2 d4 c4) + 2 c4) \\
 & (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (2 c3 d2 + 1) + \text{angle } (1 - 2 d2 c2) \\
 & (-2 c5 (1 - 2 d4 c4) + 2 c4) (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) d2 \\
 & (-2 c3 (1 - 2 d2 c2) + 2 c2) + \text{angle } (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1)^2 \\
 & (-2 c3 (1 - 2 d2 c2) + 2 c2) (1 - 2 d2 c2) (2 c3 d2 + 1) \\
 & + \text{angle } (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1)^2 (-2 c3 (1 - 2 d2 c2) + 2 c2)^2 d2 - 4 \\
 & (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (-2 c3 (1 - 2 d2 c2) + 2 c2) d2 c1 \text{ magn yob } c6 \\
 & - 4 c1 (-2 c5 (d3 + d4 (-2 c4 d3 - 1)) + 2 c4 d3 + 1) (2 c3 d2 + 1) (1 - 2 d2 c2) \text{ magn yob } c6 \\
 & + 4 \text{magn}^2 \text{ yob } c6^2 (1 - 2 d2 c2) / ((
 \end{aligned}$$

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$$\begin{aligned}
 & (-2 \ c5 \ (d3 + d4 \ (-2 \ c4 \ d3 - 1)) + 2 \ c4 \ d3 + 1) \ (1 - 2 \ d4 \ c4) \ d2 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) + 2 \ c2) \\
 & - (-2 \ c5 \ (1 - 2 \ d4 \ c4) + 2 \ c4) \ (d3 + d4 \ (-2 \ c4 \ d3 - 1)) \ d2 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) + 2 \ c2) \\
 & - (2 \ c3 \ d2 + 1) \ (1 - 2 \ d2 \ c2) \ (-2 \ c5 \ (1 - 2 \ d4 \ c4) + 2 \ c4) \ (d3 + d4 \ (-2 \ c4 \ d3 - 1)) \\
 & + (2 \ c3 \ d2 + 1) \ (1 - 2 \ d2 \ c2) \ (-2 \ c5 \ (d3 + d4 \ (-2 \ c4 \ d3 - 1)) + 2 \ c4 \ d3 + 1) \ (1 - 2 \ d4 \ c4) \\
 & (1 - 2 \ d2 \ c2) \ c6^2 \ \text{angle}
 \end{aligned}$$

6-mirror system, stop on mirror 4

[0054] Similarly, the original derivations can be used to solve the variables of a six-mirror system with the stop position on mirror four.

[0055] Again, the first solve is pupil in infinity or telecentricity in the image. The angle of the ray going through the optical axis in the stop surface should be zero in the image. The matrix from the stop surface to the fifth mirror generated by multiplication of the appropriate M matrices derived above is given by:

$$\begin{bmatrix} 1 & d4 \\ -2 \ c5 & -2 \ c5 \ d4 - 1 \end{bmatrix} \quad (55)$$

The matrix from the second mirror surface to the stop surface is given by:

$$\begin{bmatrix} 1 - 2 \ d2 \ c2 + d3 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) + 2 \ c2) & -d2 + d3 \ (2 \ c3 \ d2 + 1) \\ -2 \ c4 \ (1 - 2 \ d2 \ c2 + d3 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) + 2 \ c2)) + 2 \ c3 \ (1 - 2 \ d2 \ c2) - 2 \ c2 & -2 \ c4 \ (-d2 + d3 \ (2 \ c3 \ d2 + 1)) - 2 \ c3 \ d2 - 1 \end{bmatrix} \quad (56)$$

So, as derived above, the distance between mirror 5 and 6, solved in the appropriate matrix and the vector of distances, is:

$$d5 := \frac{1}{2} \frac{-2 \ c6 \ d4 + 2 \ c5 \ d4 + 1}{c6 \ (2 \ c5 \ d4 + 1)} \quad (57)$$

The distance between mirror one and two is:

$$\begin{aligned}
 d1 := & \frac{1}{4} (4 \ (-d2 + d3 \ (2 \ c3 \ d2 + 1)) \ c1 \ \text{magn yob } c6 - 2 \ (1 - 2 \ d2 \ c2 + d3 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) \\
 & + 2 \ c2)) \ \text{magn yob } c6 \\
 & + (1 - 2 \ d2 \ c2 + d3 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) + 2 \ c2)) \\
 & \ \text{angle}(-2 \ c5 \ d4 - 1) (-2 \ c4 \ (-d2 + d3 \ (2 \ c3 \ d2 + 1)) - 2 \ c3 \ d2 - 1) \\
 & - \text{angle}(-d2 + d3 \ (2 \ c3 \ d2 + 1)) (-2 \ c5 \ d4 - 1) (-2 \ c4 \ (1 - 2 \ d2 \ c2 + d3 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) \\
 & + 2 \ c2)) + 2 \ c3 \ (1 - 2 \ d2 \ c2) - 2 \ c2)) / (\\
 & (1 - 2 \ d2 \ c2 + d3 \ (-2 \ c3 \ (1 - 2 \ d2 \ c2) + 2 \ c2)) \ c1 \ \text{magn yob } c6)
 \end{aligned} \quad (58)$$

And the distance between the object and the first mirror:

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$$d0 := \frac{1}{2}((1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2 + 2 c2)) \text{ angle } (-2 c5 d4 - 1) (-2 c4 (-d2 + d3 (2 c3 d2 + 1)) - 2 c3 d2 - 1) \\$$

$$- \text{ angle } (-d2 + d3 (2 c3 d2 + 1)) (-2 c5 d4 - 1) (-2 c4 (1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2) \\$$

$$- 2 c1 yob (-d2 + d3 (2 c3 d2 + 1)) (-2 c5 d4 - 1) (-2 c4 (1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2) \\$$

$$+ 2 c1 yob (1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2))(-2 c5 d4 - 1)(-2 c4 (-d2 + d3 (2 c3 d2 + 1)) - 2 c3 d2 - 1) \\$$

$$- 2 (1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2)) \text{ magn yob } c6) \\$$

$$/ (\text{ angle } (-(-2 c4 (1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2) (-d2 + d3 (2 c3 d2 + 1)) \\$$

$$+ (-2 c4 (-d2 + d3 (2 c3 d2 + 1)) - 2 c3 d2 - 1) \\$$

$$(1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2))) c1 (-2 c5 d4 - 1)) \quad (59)$$

And the distance between mirror six and the image surface:

$$d6 := \frac{1}{4}(_2 \text{ angle } (1 - 2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2))^2 c6 (_2 c5 d4 - 1) \\$$

$$(_2 c4 (_2 d2 + d3 (2 c3 d2 + 1)) - 2 c3 d2 - 1) + 2 \text{ angle } \\$$

$$(1 - 2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2)) c6 (_2 c5 d4 - 1) (_2 d2 + d3 (2 c3 d2 + 1)) \\$$

$$(_2 c4 (1 - 2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2) - 4 \text{ angle } \\$$

$$(_2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2))^2 c5 c6 d4 \\$$

$$(_2 c4 (_2 d2 + d3 (2 c3 d2 + 1)) - 2 c3 d2 - 1) + 4 \text{ angle } \\$$

$$(1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2)) c5 c6 d4 (_2 d2 + d3 (2 c3 d2 + 1)) \\$$

$$(_2 c4 (_2 d2 + d3 (2 c3 d2 + 1)) - 2 c3 d2 - 1) + 2 \text{ angle } \\$$

$$(1 - 2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2)) c5 (_2 c5 d4 - 1) (_2 d2 + d3 (2 c3 d2 + 1)) \\$$

$$(_2 c4 (1 - 2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2) + \text{ angle } \\$$

$$(_2 c5 d4 - 1)^2 (_2 c4 (1 - 2 d2 c2 + d3 (_2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2) \\$$

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$$(1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) (1_2 c4 (1_2 d2 + d3 (2 c3 d2 + 1)) 1_2 c3 d2 1) 1_2$$

$$angle (1_2 c5 d4 1)^2$$

$$(1_2 c4 (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) 1_2 c2)^2$$

$$(1_2 d2 + d3 (2 c3 d2 + 1)) + 4 (1_2 c5 d4 1)$$

$$(1_2 c4 (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) 1_2 c2)$$

$$(1_2 d2 + d3 (2 c3 d2 + 1)) c1 magn yob c6 4 c1 (1_2 c5 d4 1)$$

$$(1_2 c4 (1_2 d2 + d3 (2 c3 d2 + 1)) 1_2 c3 d2 1) (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2))$$

$$magn yob c6 + 4 magn^2 yob c6^2 (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) / ((1_2$$

$$(1_2 c5 d4 1) (1_2 d2 + d3 (2 c3 d2 + 1))$$

$$(1_2 c4 (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) 1_2 c2) 1_2 c5 d4$$

$$(1_2 d2 + d3 (2 c3 d2 + 1))$$

$$(1_2 c4 (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) 1_2 c2) + 2$$

$$(1_2 c4 (1_2 d2 + d3 (2 c3 d2 + 1)) 1_2 c3 d2 1) (1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) c5$$

$$d4 + (1_2 c4 (1_2 d2 + d3 (2 c3 d2 + 1)) 1_2 c3 d2 1)$$

$$(1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) (1_2 c5 d4 1)$$

$$(1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) c6^2 angle \quad (60)$$

6-mirror system, stop on mirror 5

[0056] Again, we use the original derivations to solve the variables of a six-mirror system with the stop position on mirror five. As before, the first solve is pupil in infinity or telecentricity in the image. The angle of the ray going through the optical axis in the stop surface should be zero in the image. The matrix from the stop surface to the fifth mirror generated by multiplication of the appropriate M matrices derived above is given by:

$$\begin{bmatrix} 1 & 0 \\ 0 & 1 \end{bmatrix}$$

(61)

The matrix from the second mirror surface to the stop surface is given by:

$$[1_2 d2 c2 + d3 (1_2 c3 (1_2 d2 c2) + 2 c2) + d4 (1_2 c4 (1_2 d2 c2 +$$

$$d3 (1_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) 1_2 c2),$$

$$1_2 d2 + d3 (2 c3 d2 + 1) + d4 (1_2 c4 (1_2 d2 +$$

$$d3 (2 c3 d2 + 1)) 1_2 c3 d2 1)]$$

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$$\begin{aligned}
 & _2 c5 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) _2 c2)) \\
 & + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2)) _2 c3 (1_2 d2 c2) + 2 c2, \\
 & 2 c5 (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1)) _2 c3 d2 _1)) \\
 & + 2 c4 (_d2 + d3 (2 c3 d2 + 1)) + 2 c3 d2 + 1] \quad (62)
 \end{aligned}$$

So, as derived above, the distance between mirror 5 and 6, solved in the appropriate matrix and the vector of distances is:

$$d5 := -\frac{1}{2} \frac{1}{c6} \quad (63)$$

The distance between mirror one and two was:

$$\begin{aligned}
 d1 := & -\frac{1}{4} (4 (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1)) \\
 & - 2 c3 d2 _1)) c1 magn yob c6 \\
 & - 2 (1_2 d2 c2 + d3 (-2 c3 (1_2 d2 c2) + 2 c2) + d4 (-2 c4 (1_2 d2 c2 + \\
 & d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) _2 c2)) magn yob c6 + \\
 & (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + \\
 & d4 (_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + \\
 & 2 c3 (1_2 d2 c2) _2 c2)) angle \\
 & (_2 c5 (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + \\
 & d3 (2 c3 d2 + 1)) _2 c3 d2 _1)) + 2 c4 (_d2 + d3 (2 c3 d2 + 1)) + 2 c3 d2 + 1) _ angle \\
 & (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + \\
 & d3 (2 c3 d2 + 1)) _2 c3 d2 _1)) (\\
 & -2 c5 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) _2 c2)) \\
 & + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2)) _2 c3 (1_2 d2 c2) + 2 c2)) / (\\
 & (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & d3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2) _2 c2)) c1 magn yob c6) \quad (64)
 \end{aligned}$$

And the distance between the object and the first mirror:

$$\begin{aligned}
 d0 := & -\frac{1}{2} ((1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2) \\
 & + d4 (-2 c4 (1 - 2 d2 c2 + d3 (-2 c3 (1 - 2 d2 c2) + 2 c2)) + 2 c3 (1 - 2 d2 c2) - 2 c2)) angle
 \end{aligned}$$

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$$\begin{aligned}
 & (-2 \text{ c5 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + d4 (-2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 & \quad + 2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + 2 \text{ c3 } d2 + 1) \\
 5 \quad & - \text{ angle } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + d4 (-2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 & \quad (-2 \text{ c5 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c2}) \\
 10 \quad & + d4 (-2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1 - 2 \text{ d2 } c2) - 2 \text{ c2})) \\
 & \quad + 2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) - 2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2}) \\
 & - 2 \text{ c1 yob } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + d4 (-2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 15 \quad & \quad (-2 \text{ c5 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c2}) \\
 & \quad + d4 (-2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1 - 2 \text{ d2 } c2) - 2 \text{ c2})) \\
 20 \quad & + 2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) - 2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2}) + 2 \text{ c1 yob } \\
 & \quad (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + \\
 & \quad d4 (-2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1 - 2 \text{ d2 } c2) - 2 \text{ c2})) \\
 25 \quad & \quad (-2 \text{ c5 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + d4 (-2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 & \quad + 2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + 2 \text{ c3 } d2 + 1) - 2 (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) \\
 30 \quad & + d4 (-2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1 - 2 \text{ d2 } c2) - 2 \text{ c2})) \text{ magn yob c6}) \\
 & \quad / (\text{ angle } (-2 \text{ c5 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c2})) \\
 & \quad + d4 (-2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1 - 2 \text{ d2 } c2) - 2 \text{ c2})) \\
 35 \quad & \quad + 2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) - 2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2}) \\
 & \quad (-d2 + d3 (2 \text{ c3 } d2 + 1)) + d4 (-2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 40 \quad & \quad + (-2 \text{ c5 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + d4 (-2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 & \quad + 2 \text{ c4 } (-d2 + d3 (2 \text{ c3 } d2 + 1)) + 2 \text{ c3 } d2 + 1)(1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) \\
 & \quad + d4 (-2 \text{ c4 } (1 - 2 \text{ d2 } c2 + d3 (-2 \text{ c3 } (1 - 2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1 - 2 \text{ d2 } c2) - 2 \text{ c2})) \text{ c1}) \quad (65)
 \end{aligned}$$

And the distance between mirror six and the image surface:

$$\begin{aligned}
 d6 & := -\frac{1}{4} (\text{ angle } \\
 50 \quad & (1_2 \text{ d2 } c2 + d3 (1_2 \text{ c3 } (1_2 \text{ d2 } c2) + 2 \text{ c2}) + d4 (1_2 \text{ c4 } (1_2 \text{ d2 } c2 + \\
 & \quad d3 (1_2 \text{ c3 } (1_2 \text{ d2 } c2) + 2 \text{ c2})) + 2 \text{ c3 } (1_2 \text{ d2 } c2) - 2 \text{ c2}))^2 \text{ c6} \\
 55 \quad & (1_2 \text{ c5 } (1_2 \text{ d2 } + d3 (2 \text{ c3 } d2 + 1)) + d4 (1_2 \text{ c4 } (1_2 \text{ d2 } + d3 (2 \text{ c3 } d2 + 1)) - 2 \text{ c3 } d2 - 1)) \\
 & \quad + 2 \text{ c4 } (1_2 \text{ d2 } + d3 (2 \text{ c3 } d2 + 1)) + 2 \text{ c3 } d2 + 1) + 2 \text{ angle}
 \end{aligned}$$

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$$\begin{aligned}
 & (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) \\
 & \quad + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) c6 \\
 5 & \quad (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) (\\
 & \quad _2 c5 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) \\
 10 & \quad + d4 (_2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2 + - 2 c2) \\
 & \quad + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) \\
 & \quad + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) \\
 15 & \quad + 2 c2))_2 c3 (1_2 d2 c2) + 2 c2) + angle(\\
 & \quad _2 c5 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) \\
 20 & \quad + d4 (_2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) \\
 & \quad + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2))_2 c3 (1_2 d2 c2) + 2 c2) \\
 & \quad (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 25 & \quad d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) \\
 & \quad (_2 c5 (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) \\
 30 & \quad + 2 c4 (_d2 + d3 (2 c3 d2 + 1)) + 2 c3 d2 + 1)_angle(\\
 & \quad _2 c5 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & \quad d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) \\
 35 & \quad + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2))_2 c3 (1_2 d2 c2) + 2 c2)^2 \\
 & \quad (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) + 4(\\
 40 & \quad _2 c5 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & \quad d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) \\
 & \quad + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2))_2 c3 (1_2 d2 c2) + 2 c2) \\
 45 & \quad (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) c1 magn yob c6_4 c1 \\
 & \quad (_2 c5 (_d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) \\
 50 & \quad + 2 c4 (_d2 + d3 (2 c3 d2 + 1)) + 2 c3 d2 + 1) \\
 & \quad (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & \quad d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2)_2 c2)) magn yob c6 \\
 55 & \quad + 4 magn^2 yob c6^2 \\
 & \quad (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2)
 \end{aligned}$$

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$$\begin{aligned}
 & + 2 c2)) + 2 c3(1_2 d2 c2_2 c2)))/((- (\\
 & _2 c5(1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + \\
 & d4 (_2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2_2 c2)) \\
 & + 2 c4 (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2))_2 c3(1_2 d2 c2) + 2 c2) \\
 & (_2 d2 + d3(2 c3 d2 + 1) + d4 (_2 c4 (_2 d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) + \\
 & (_2 c5 (_2 d2 + d3 (2 c3 d2 + 1) + d4 (_2 c4 (_2 d2 + d3 (2 c3 d2 + 1))_2 c3 d2_1)) \\
 & + 2 c4 (_2 d2 + d3 (2 c3 d2 + 1)) + 2 c3 d2 + 1) \\
 & (1_2 d2 c2 + d3 (_2 c3(1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3(1_2 d2 c2_2 c2))) \\
 & (1_2 d2 c2 + d3 (_2 c3 (1_2 d2 c2) + 2 c2) + d4 (_2 c4 (1_2 d2 c2 + \\
 & d3 (_2 c3 (1_2 d2 c2) + 2 c2)) + 2 c3 (1_2 d2 c2_2 c2)) c6^2 angle) \tag{66}
 \end{aligned}$$

4-mirror system, stop on mirror 2

[0057] Yet again, we can use these derivations to solve the variables of a four-mirror system with the stop position on mirror two. As usual, the first solve is pupil in infinity or telecentricity in the image. The angle of the ray going through the optical axis in the stop surface should be zero in the image. The matrix from the stop surface to the third mirror generated by multiplication of the appropriate M matrices derived above, is given by:

$$\begin{bmatrix} 1 & d2 \\ _2 c3 & _2 c3 d2 _1 \end{bmatrix} \tag{67}$$

The matrix from the second mirror surface to the stop surface is given by:

$$\begin{bmatrix} 1 & 0 \\ _2 c2 & _1 \end{bmatrix} \tag{68}$$

So as derived above, the distance between mirror 3 and 4, solved in the appropriate matrix and the vector of distances is:

$$d3 := \frac{1}{2} \frac{_2 c4 d2 + 2 c3 d2 + 1}{c4 (2 c3 d2 + 1)} \tag{69}$$

The distance between mirror one and two was:

$$d1 := \frac{1}{4} \frac{2 \text{ magn yob } c4_angle(_2 c3 d2_1)}{c1 \text{ magn yob } c4} \tag{70}$$

And the distance between the object and the first mirror:

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$$d0 := \frac{1}{2} \frac{-\text{angle} (-2 \text{ c3 } d2_1) - 2 \text{ c1 } \text{yob} (-2 \text{ c3 } d2_1) - 2 \text{ magn } \text{yob } c4}{\text{angle } c1 (-2 \text{ c3 } d2_1)} \quad (71)$$

And the distance between mirror four and the image surface:

$$d4 := \frac{1}{4} (2 \text{ angle } c4 (-2 \text{ c3 } d2_1) + 4 \text{ angle } c3 c4 d2 + 2 \text{ angle } c3 (-2 \text{ c3 } d2_1) + 2 \text{ angle } (-2 \text{ c3 } d2_1)^2 c2 + 4 \text{ c1 } (-2 \text{ c3 } d2_1) \text{ magn } \text{yob } c4 + 4 \text{ magn}^2 \text{ yob } c4^2) / (c4^2 \text{ angle}) \quad (72)$$

4-mirror system, stop on mirror 3

[0058] Again, we use the original derivations to solve the variables of a four-mirror system with the stop position on mirror three. The first solve is pupil in infinity or telecentricity in the image.

The angle of the ray going through the optical axis in the stop surface should be zero in the image. The matrix from the stop surface to the third mirror generated by multiplication of the appropriate M matrices derived above is given by:

$$\begin{bmatrix} 1 & 0 \\ 0 & 1 \end{bmatrix} \quad (73)$$

The matrix from the second mirror surface to the stop surface is given by:

$$\begin{bmatrix} 1 - 2 d2 c2 & -d2 \\ -2 c3 (1 - 2 d2 c2) + 2 c2 & 2 c3 d2 + 1 \end{bmatrix} \quad (74)$$

So as we derived the distance between mirror 3 and 4 is:

$$d3 := \frac{1}{2} \frac{1}{c4} \quad (75)$$

And we solve this new found value in the appropriate matrix and the vector of distances. The distance between mirror one and two was:

$$d1 := -\frac{1}{4} \frac{-4 d2 c1 \text{ magn } \text{yob } c4 - 2 (1 - 2 d2 c2) \text{ magn } \text{yob } c4 + (1 - 2 d2 c2) \text{ angle } (2 c3 d2 + 1) + \text{angle } d2 (-2 c3 (1 - 2 d2 c2) + 2 c2)}{(1 - 2 d2 c2) c1 \text{ magn } \text{yob } c4}$$

(76)

And the distance between the object and the first mirror:

$$d0 := -\frac{1}{2} ((1 - 2 d2 c2) \text{ angle } (2 c3 d2 + 1) + \text{angle } d2 (-2 c3 (1 - 2 d2 c2) + 2 c2) + 2 c1 \text{ yob } d2 (-2 c3 (1 - 2 d2 c2) + 2 c2) + 2 c1 \text{ yob } (1 - 2 d2 c2) (2 c3 d2 + 1) - 2 (1 - 2 d2 c2) \text{ magn } \text{yob } c4) / (\text{angle } ((-2 c3 (1 - 2 d2 c2) + 2 c2) d2 + (2 c3 d2 + 1) (1 - 2 d2 c2)) c1) \quad (77)$$

And the distance between mirror four and the image surface:

$$\begin{aligned}
 d4 := & -\frac{1}{4} (_2 \text{ angle } (1_2 d2 c2)^2 c4 (2 c3 d2 + 1) \\
 & _2 \text{ angle } (1_2 d2 c2) c4 d2 (_2 c3 (1_2 d2 c2) + 2 c2) \\
 & + \text{angle } (_2 c3 (1_2 d2 c2) + 2 c2) (1_2 d2 c2) (2 c3 d2 + 1) \\
 & + \text{angle } (_2 c3 (1_2 d2 c2) + 2 c2)^2 d2_4 (_2 c3 (1_2 d2 c2) + 2 c2) d2 c1 \text{ magn yob } c4 \\
 & _4 c1 (2 c3 d2 + 1) (1_2 d2 c2) \text{ magn yob } c4 + 4 \text{ magn}^2 \text{ yob } c4^2 (1_2 d2 c2)) / (\\
 & ((_2 c3 (1_2 d2 c2) + 2 c2) d2 + (2 c3 d2 + 1) (1_2 d2 c2)) (1_2 d2 c2) c4^2 \text{ angle}) \quad (78)
 \end{aligned}$$

Obscuration

[0059] A particular problem in designing mirror systems, not encountered in refractive lens systems, is ensuring that the beam is not obscured in its zigzag course by other mirrors. Because of the necessary zigzag path, as the projection beam proceeds between successive mirrors I and I+1 on the optical path in many cases it will pass by at least one other mirror J. Thus, for an optical system not to be obscured it is necessary to ensure that the position and extent of the intervening mirror J is such that it does not intersect any part of the beam between mirrors I and I+1. This is shown in Figure 4 in which it can be seen that mirror J lies wholly below the beam between I and I+1 whereas mirror J' partially intersects the beam. The arrangement of mirror J is not permitted.

[0060] In a model of a potential projection system, obscuration can be detected by the following procedure:

1. For each pair of successive mirrors I, I+1 on the optical path, check if there exists a mirror J (with J not equal to I, I+1) having a position on the optical axis (Z axis) between I and I+1
2. If J exists, calculate the distance from the optical axis (Y position) of the extreme rays from I to I+1 at the position of mirror J on the optical axis.
3. Check that the top and bottom of mirror J are both above (i.e. have greater Y position) or both below (i.e. have smaller Y position) both the extreme rays from I to I+1.

If the check in (3) fails, then mirror J at least partially obscures the beam from I to I+1 and the mirror system must be modified or rejected.

Preferred four-mirror systems

[0061] Figure 6 shows a mirror system in class 9(+) which can be used in the lithography apparatus of Figure 1. In this class, the stop can be positioned on mirror 2 or 3; in the system of Figure 6, the stop position is on surface 2. The ring field of this system is defined on the object side, between 114 and 118 arbitrary units, with a numerical aperture of 0.25 (0.05 on the object side). The magnification is 0.2 and an intermediate image is formed between mirrors 3 and 4. The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 1 below. The values found for the curvatures and thicknesses can be re-scaled using a scaling factor. If the thicknesses are multiplied by that factor, the curvatures should be divided by it, and vice versa.

[0062] Figure 7 also shows a mirror system in class 9(+). In this case the stop is on mirror 3 and the intermediate image is between mirrors 1 and 2. The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 2 below.

[0063] Figure 8 shows an example of a class 2(-) system having the stop located on the third mirror. From the object (mask MA, surface 0) all the rays go, with a negative angle (a zero angle is parallel to the optical axis), to the first convex mirror M₁. The convex mirror M₁ reflects the beam upward to a large concave mirror M₂. The position of the second mirror M₂ has to be above the beam between the object (mask MA) and mirror M₁. The beam then goes under mirror M₁ to the stop surface mirror M₃. From the stop surface the beam is reflected to concave mirror M₄. Mirror M₄ takes care of a telecentric illumination of the image (surface 5). The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 3 below.

[0064] A class 6(-) system, shown in Figure 9, consists of two mirror pairs, in a symmetrical design. From the object (mask MA, surface 0) all the rays go, with a negative angle (a zero angle is parallel to the optical axis), to the first convex mirror M₁. The object is illuminated as telecentric as possible, this being a requirement for lithography. The

convex mirror M_1 reflects the beam upward to a large concave mirror M_2 . The position of this mirror has to be above the beam between the object and mirror M_1 . So far this design resembles the class 2(-) design (shown in Figure 8). The beam then goes over mirror M_1 to the stop surface on mirror M_3 , limited by the top of mirror M_1 . From the stop surface M_3 the beam is reflected to concave mirror M_4 . Mirror M_4 takes care of a telecentric illumination of the image (surface 5). The ring field of this system is defined on the image side, between -22.8 and -23.8, resulting in a Strehl ratio of at least 0.972 with a numerical aperture of 0.15. The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 4 below.

[0065] A class 9(-) system with a stop on the second surface is shown in Figure 10. The ring field of this system is defined on the object side, between 114 and 118 arbitrary units, with a numerical aperture of 0.2 (0.05 on the object side). The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 5 below.

[0066] Figure 11 shows a system in class 10(-). The ring field of this system is defined on the object side, between 114 and 118 arbitrary units, with a numerical aperture of 0.2 (0.05 on the object side). The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 6 below.

Preferred six-mirror systems

[0067] All the six-mirror systems found to be feasible have, as they have a positive magnification, an intermediate image.

[0068] Figure 12 shows a six-mirror system in class 9(+) in which the stop can be positioned on mirror 2, 3, 4 and 5. The system has the intermediate image located between mirror 2 and five. The ring field of this system is defined on the object side, between 114 and 118 arbitrary units, with a numerical aperture of 0.24 (0.06 on the object side). The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 7 below.

[0069] A class 37(+) six-mirror system can have the stop positioned on mirror 2, 3, 4 or 5 and has the intermediate image located between mirror 2 and five. The ring field of such a system is defined on the image side, between 27 and 30 arbitrary units, with a numerical aperture of 0.24.

[0070] The system shown in Figure 13 has the stop on surface 2. This system consists of a mirror pair near the object and four-mirrors grouped near the image. From the object (mask MA, surface 0) all the rays go, with a negative angle, to the first concave mirror M_1 . The concave mirror M_1 reflects the beam downward to mirror M_2 which is almost flat. The top of mirror M_2 is restricted to be below the beam between the object and mirror M_1 . The beam between mirror M_2 and M_3 limits the bottom of the small mirror M_4 , whilst the beam between mirror M_4 and M_5 limits the top of mirror M_4 . Finally, the beam between the last mirror M_6 and the image limits the top of mirror M_5 . The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 8 below.

[0071] For comparison, Figure 14 shows a class 37(+) six-mirror system with the stop on surface 5. The ring field of this system is defined on the image side, between 27 and 30 arbitrary units, with a numerical aperture of 0.24. The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 9 below.

Preferred eight-mirror system

[0072] An eight-mirror system in class 165(+) with stop on surface 3 is shown in Figure 15. The ring field of this system is defined on the object side, between 116 and 124 arbitrary units, with a numerical aperture of 0.24 (0.06 on the object side). The first order curvatures and thicknesses of this system, in arbitrary units, are given in Table 10 below.

[0073] An eight mirror system in class 169(+) is shown in Figure 16, the curvatures and thicknesses of its elements are shown in Table 11. This system has a ring field in the object side between 114 and 118 arbitrary units, a numerical aperture of 0.4, distortion <2.9 nm and an rms wavefront error <0.3 λ .

[0074] An eight mirror system in class 181(+) is shown in Figure 17, the curvatures and thicknesses of its elements are shown in Table 12. Again, the ring field on the object side is between 114 and 118 units and the numerical aperture is 0.4. However, the distortion is < 1.9 nm and the rms wavefront error <0.5 λ .

[0075] An eight mirror system in class 150(-) is shown in Figure 18, the curvatures and thicknesses of its elements are shown in Table 13. This system provides a distortion <2.6 nm and an rms wavefront error <0.19 λ .

[0076] An eight mirror system in class 182(-) is shown in Figure 19, the curvatures and thicknesses of its elements are shown in Table 14. This system likewise has a ring field on the object side between 114 and 118 arbitrary units, a numerical aperture of 0.4, an rms wavefront error of <1 λ and a distortion <2.18 nm.

[0077] Whilst we have described above specific embodiments of the invention it will be appreciated that the invention may be practiced otherwise than described. The description is not intended to limit the invention.

Table 1

	Curvature		Thickness
		d_0	834.233264
c_1	-0.00014266	d_1	-599.763693
c_2	0.00088498	d_2	684.179623
c_3	-0.00998244	d_3	-83.415929
c_4	0.01918223	d_4	61.797248
		d_5	16.018048

Table 4

	Curvature		Thickness
		d_0	767.692000
c_1	0.00300902	d_1	-642.472629
c_2	0.00095506	d_2	1445.239615
c_3	0.00407728	d_3	-78.092188
c_4	0.00607760	d_4	94.620253
		d_5	-1.961967

Table 2

	Curvature		Thickness
		d_0	616.993869
c_1	-0.00243396	d_1	-633.892913
c_2	0.00190431	d_2	636.600251
c_3	0.00025705	d_3	-69.291720
c_4	0.00724502	d_4	64.788741
		d_5	4.467388

Table 5

	Curvature		Thickness
		d_0	449.444384
c_1	-0.00042724	d_1	-396.786263
c_2	-0.00168067	d_2	403.457960
c_3	-0.00659922	d_3	-67.000191
c_4	-0.01721598	d_4	54.629940
		d_5	4.695013

Table 3

	Curvature		Thickness
		d_0	359.695357
c_1	0.00152836	d_1	-274.181525
c_2	0.00259323	d_2	261.925120
c_3	0.01867917	d_3	-26.735917
c_4	0.01765947	d_4	48.776080
		d_5	-0.416277

Table 6

	Curvature		Thickness
		d_0	444.844414
c_1	-0.00256672	d_1	-83.893940
c_2	-0.00023614	d_2	80.638988
c_3	0.01329749	d_3	-42.956528
c_4	0.01099286	d_4	93.755560
		d_5	-0.762586

Table 7

	Curvature		Thickness
		d_0	131.380868
c_1	0.00289128	d_1	-113.331683
c_2	0.00499283	d_2	146.579813
c_3	0.00863830	d_3	-93.218415
c_4	0.01007555	d_4	88.970994
c_5	0.01220780	d_5	-93.941281
c_6	0.00873868	d_6	116.487572
		d_7	-0.127679

Table 9

	Curvature		Thickness
		d_0	405.798032
c_1	-0.00475154	d_1	-64.654405
c_2	-0.00852932	d_2	487.659410
c_3	-0.00286217	d_3	-202.163489
c_4	-0.00307574	d_4	230.915333
c_5	0.00000503	d_5	-116.766023
c_6	0.00422514	d_6	189.881646
		d_7	0.000000

Table 8

	Curvature		Thickness
		d_0	828.570000
c_1	-0.00111627	d_1	-304.777604
c_2	-0.00007435	d_2	680.858425
c_3	-0.00238747	d_3	-160.275601
c_4	-0.00019501	d_4	124.017066
c_5	0.00719636	d_5	-145.964808
c_6	0.00467166	d_6	231.541247
		d_7	0.075648

Table 10

	Curvature		Thickness
		d_0	322.380000
c_1	-0.00178490	d_1	-108.516829
c_2	-0.00245113	d_2	174.110025
c_3	-0.00202694	d_3	-168.774787
c_4	-0.00124407	d_4	983.268141
c_5	-0.00183868	d_5	-213.604816
c_6	-0.00200081	d_6	274.820705
c_7	0.00126629	d_7	-197.754689
c_8	0.00476144	d_8	160.164412
		d_9	0.000000

Table 11

	Curvature		Thickness
		d_0	420.601299
c_1	-0.00323603	d_1	-125.470789
c_2	-0.00902233	d_2	110.112590
c_3	-0.00206939	d_3	-160.044449
c_4	0.00036641	d_4	258.697858
c_5	0.00126054	d_5	-279.043974
c_6	0.00146300	d_6	905.704090
c_7	0.00275699	d_7	-111.254872
c_8	0.00673385	d_8	112.775777
		d_9	0

Table 13

	Curvature		Thickness
		d_0	713.868812
c_1	-0.00187689	d_1	-225.978195
c_2	-0.00045910	d_2	871.620787
c_3	-0.00138063	d_3	-601.119900
c_4	-0.00002434	d_4	269.267756
c_5	0.00166695	d_5	-342.201234
c_6	0.00162141	d_6	807.574290
c_7	0.00773514	d_7	-167.796714
c_8	0.00506893	d_8	169.913678
		d_9	0

Table 12

	Curvature		Thickness
		d_0	455.886404
c_1	-0.00355263	d_1	-116.531978
c_2	-0.00563559	d_2	515.664329
c_3	-0.00151867	d_3	-282.841809
c_4	0.00151480	d_4	89.911348
c_5	0.00127162	d_5	-49.006196
c_6	-0.00070814	d_6	152.535737
c_7	0.00667355	d_7	-82.044394
c_8	0.00867329	d_8	98.259942
		d_9	0.267746

Table 14

	Curvature		Thickness
		d_0	84.702306
c_1	-0.00487728	d_1	-49.028673
c_2	-0.01142777	d_2	677.956498
c_3	-0.00154677	d_3	-710.120744
c_4	0.00369184	d_4	305.647599
c_5	0.00218954	d_5	-323.556990
c_6	0.00163258	d_6	878.491460
c_7	0.00460099	d_7	-136.990287
c_8	0.00616448	d_8	137.341290
		d_9	0

Claims

1. A lithographic projection apparatus comprising:

- a radiation system for providing a projection beam of radiation;
- a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
- a substrate table for holding a substrate;
- a projection system for projecting the patterned beam onto a target portion of the substrate,

characterized in that:

said projection system has precisely four imaging mirrors in the optical path of the projection beam and has an incidence angle classification, C, of 2(-), 6(-), or 9(-), where:

$$C = \sum_{i=1}^4 a_i \cdot 2^{(4-i)} \left(\frac{M}{|M|} \right)$$

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,
 $a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,
 M is the magnification of the projection system, and
 the index i numbers the mirrors from object to image.

2. Apparatus according to claim 1 wherein said projection system has a stop on the second or third mirror.
3. Apparatus according to claim 1 or 2 wherein said projection system has an intermediate image between the first and second mirrors, between the second and third or between the third and fourth mirrors.
4. A lithographic projection apparatus comprising:

a radiation system for providing a projection beam of radiation;
 a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
 a substrate table for holding a substrate;
 a projection system for projecting the patterned beam onto a target portion of the substrate,

characterized in that:

said projection system has precisely six imaging mirrors in the optical path of the projection beam and has an incidence angle classification, C, of 5(+), 6(-), 9(+), 13(+), 18(-), 21(+), 22(-), 25(+), 29(+), 34(-), 37(+), 38(-), 42(-), or 54(-), where:

$$C = \sum_{i=1}^6 a_i \cdot 2^{(6-i)} \left(\frac{M}{|M|} \right)$$

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,
 $a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,
 M is the magnification of the projection system, and
 the index i numbers the mirrors from object to image.

5. Apparatus according to claim 5, wherein said projection system has a stop located on the second, third, fourth or fifth mirror.
6. Apparatus according to claim 4 or 5, wherein said projection system has an intermediate image between the second and fifth mirror.
7. A lithographic projection apparatus comprising:

a radiation system for providing a projection beam of radiation;
 a support structure for supporting patterning means, the patterning means serving to pattern the projection beam according to a desired pattern;
 a substrate table for holding a substrate;
 a projection system for projecting the patterned beam onto a target portion of the substrate,

characterized in that:

said projection system has precisely eight imaging mirrors in the optical path of the projection beam and has an incidence angle classification, C, of 2(+), 5(+), 9(+), 12(+), 13(+), 18(+), 18(-), 19(+), 20(+), 21(+), 22(+), 23(+), 25(+), 26(+), 34(-), 36(+), 37(+), 38(-), 45(+), 46(+), 49(+), 52(+), 53(+), 54(+), 54(-), 55(-), 58(-), 68(+), 69(+), 73(+), 74(+), 77(+), 82(+), 82(-), 85(+), 88(+), 89(+), 90(-), 92(+), 93(+), 97(+), 100(-), 101(+), 102(-), 104(+), 105(+), 106(+), 106(-), 107(+), 108(+), 109(+), 109(-), 110(+), 110(-), 111(+), 113(+), 116(+), 117(+), 118(+), 118(-), 120(+), 121(+), 122(-), 123(-), 132(+), 133(+), 134(-), 137(+), 138(+), 141(+), 145(+), 145(-), 146(+), 146(-), 147(+), 148(+), 148(-), 149(+), 150(+), 150(-), 151(+), 151(-), 152(-), 153(+), 154(+), 154(-), 155(+), 155(-), 156(+), 157(+), 159(+), 161(+), 162(-), 163(-), 164(+), 165(+), 166(+), 166(-), 167(+), 168(+), 169(+), 170(+), 170(-), 171(+), 172(+), 173(+), 174(+), 175(+), 176(+), 177(+), 178(-), 179(+), 180(+), 180(-), 181(+), 181(-), 182(+), 182(-), 183(+), 183(-), 184(+), 185(+), 185(-), 186(-), 187(+), 187(-), 188(-), 189(+), 196(+), 197(+), 201(+), 203(+), 205(+), 209(+), 214(-), 216(+), 217(+), 218(+), 218(-), 225(+), 228(+), 229(+), 230(+), 232(+), 233(+), 235(+), 236(+), 237(+), 238(-), 243(+), 246(+), 247(+), 248(+), 250(-), where:

$$C = \sum_{i=1}^8 a_i \cdot 2^{(8-i)} \left(\frac{M}{|M|} \right)$$

$a_i = 1$ if the angle of incidence of the chief ray at mirror i is negative,

$a_i = 0$ if the angle of incidence of the chief ray at mirror i is positive,

M is the magnification of the projection system, and

the index i numbers the mirrors from object to image.

8. Apparatus according to any one of the preceding claims wherein said projection system has the smallest deviation from telecentricity whilst still enabling obscuration-free illumination of the mask such that, for each point on the object, in the pencil of rays leaving the object, the ray forming the smallest angle with the optical axis forms an angle not larger than 10° to the optical axis.
9. Apparatus according to any one of the preceding claims wherein said projection is substantially telecentric on the image side such that for each point on the object, the ray passing through the center of the aperture stop forms in the image space an angle with the optical axis not larger than 1° .
10. Apparatus according to any one of the preceding claims wherein each mirror in said projection system is substantially rotationally symmetric about an optical axis.
11. Apparatus according to any one of the preceding claims wherein said projection system has a magnification whose absolute value is in the range of from $1/3$ to $1/10$ and preferably substantially equal to $1/4$ or $1/5$.
12. Apparatus according to any one of the preceding claims wherein said projection beam comprises extreme ultra-violet radiation, e.g. having a wavelength in the range of from 8 to 20nm, preferably 9 to 16nm.
13. An apparatus according to any one of the preceding claims, wherein the support structure comprises a mask table for holding a mask.
14. An apparatus according to any one of the preceding claims, wherein the radiation system comprises a radiation source.
15. A device manufacturing method comprising the steps of:

providing a substrate that is at least partially covered by a layer of radiation-sensitive material;

providing a projection beam of radiation using a radiation system;

using patterning means to endow the projection beam with a pattern in its cross-section;

projecting the patterned beam of radiation onto a target portion of the layer of radiation-sensitive material;

characterized in that:

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in the step of imaging, a projection system as defined in any one of the preceding claims is used.

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Fig. 1

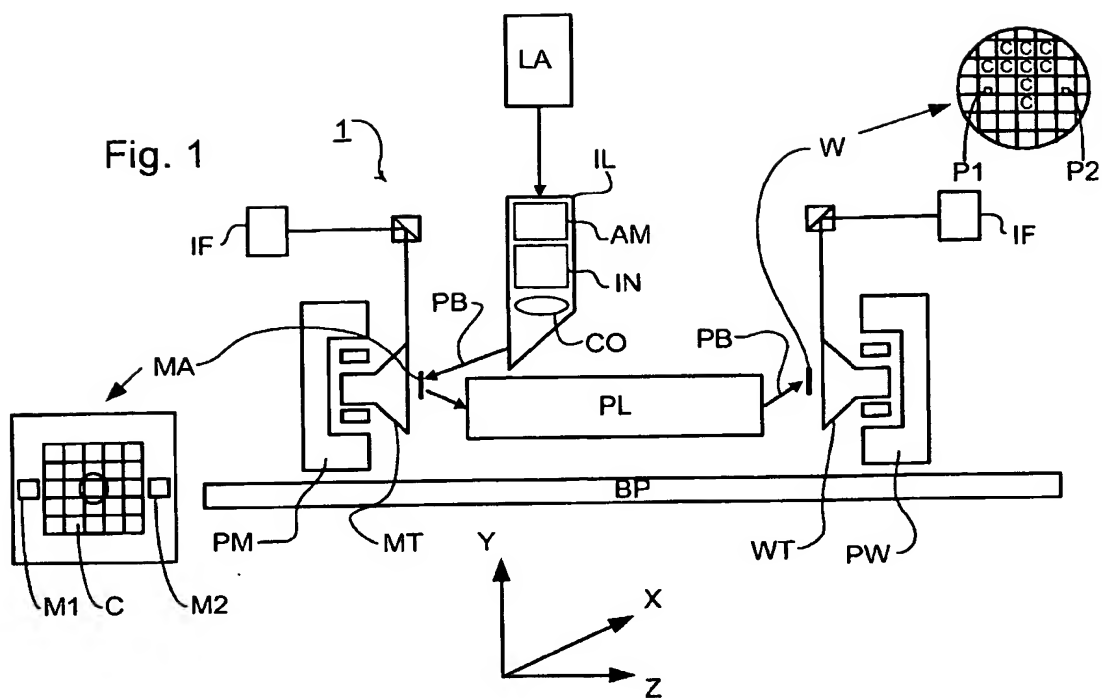


Fig. 2

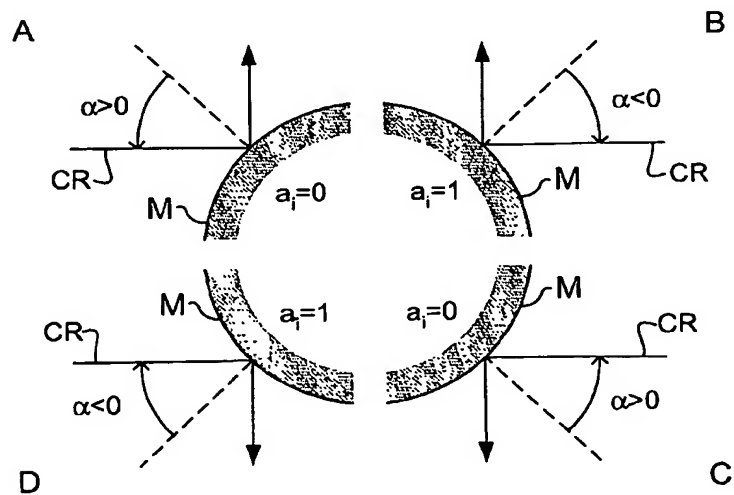


Fig. 3

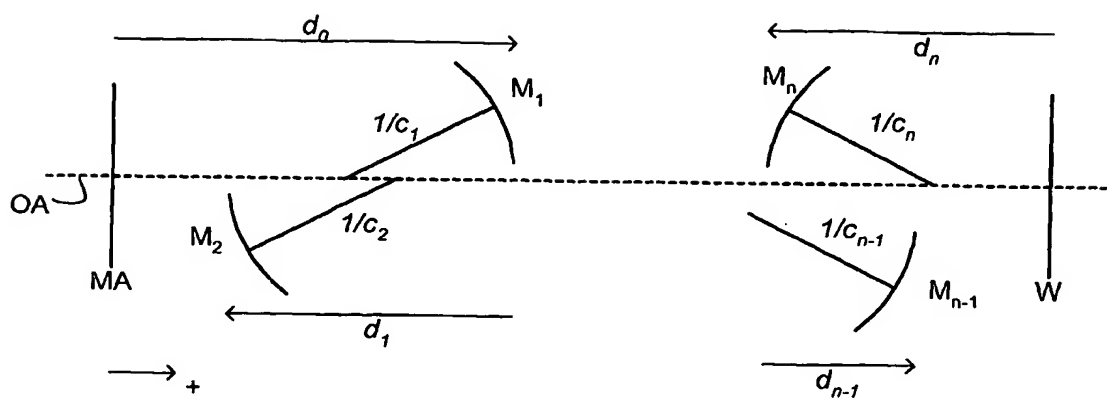


Fig. 4

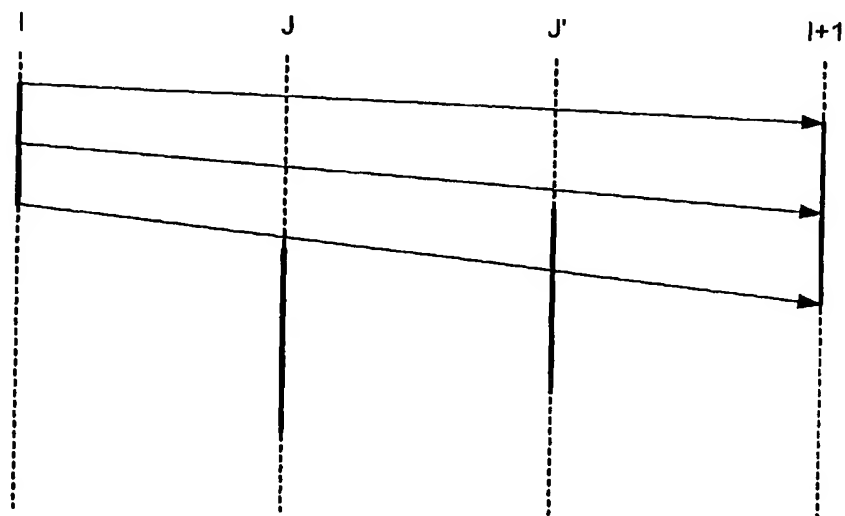


Fig. 5

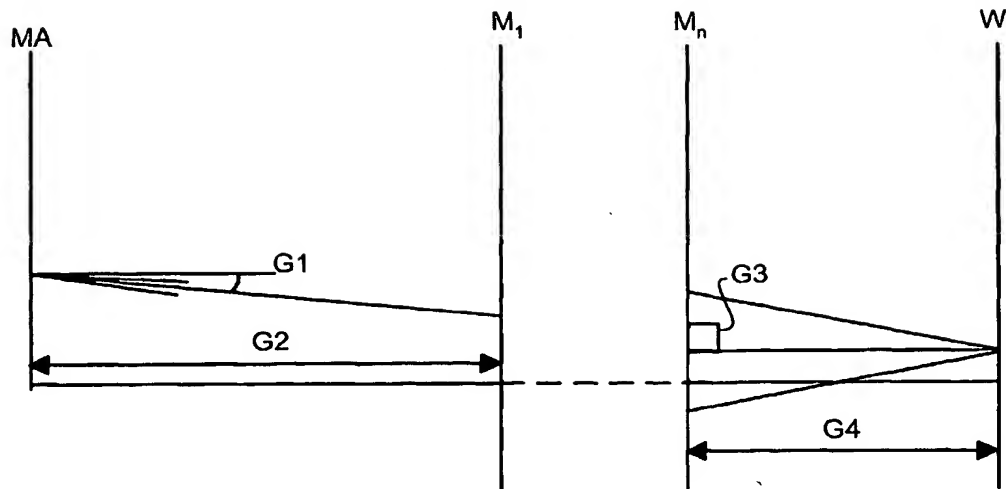


Fig. 6

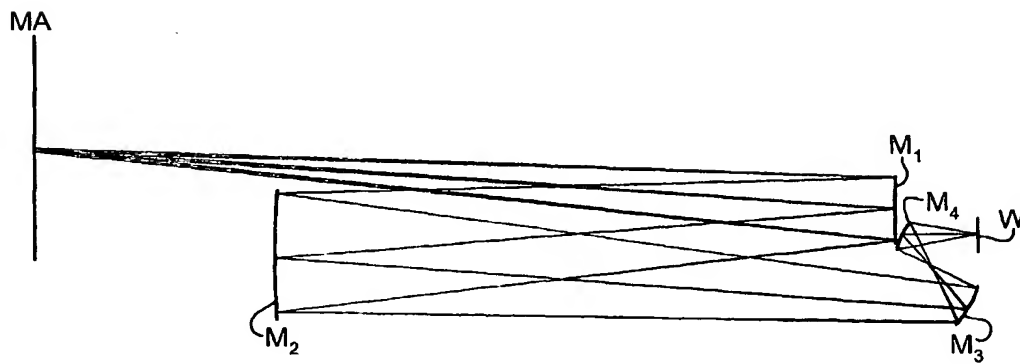


Fig. 7

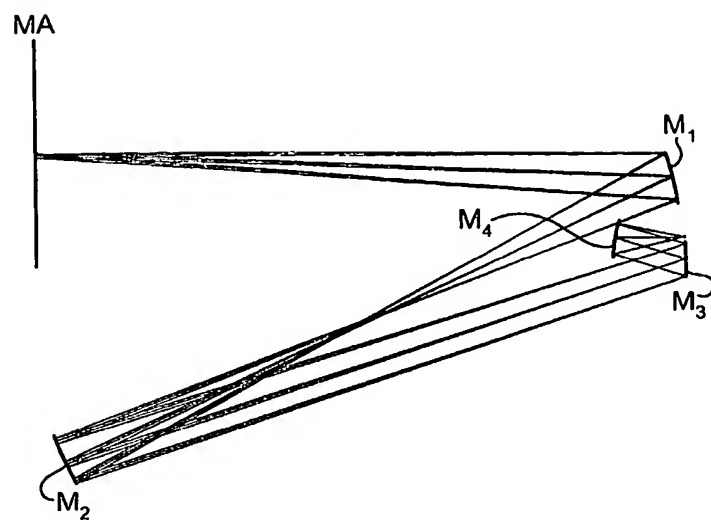


Fig. 8

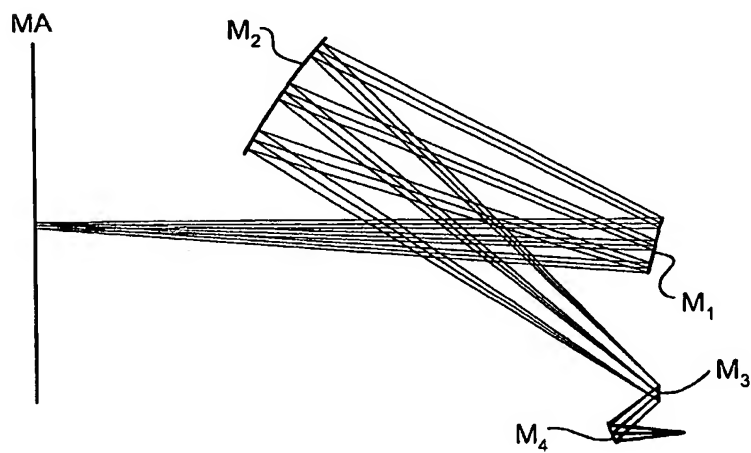


Fig. 9

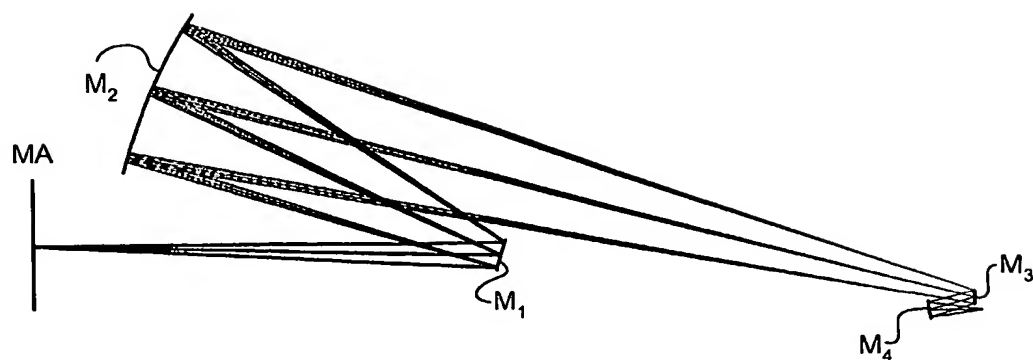


Fig. 10

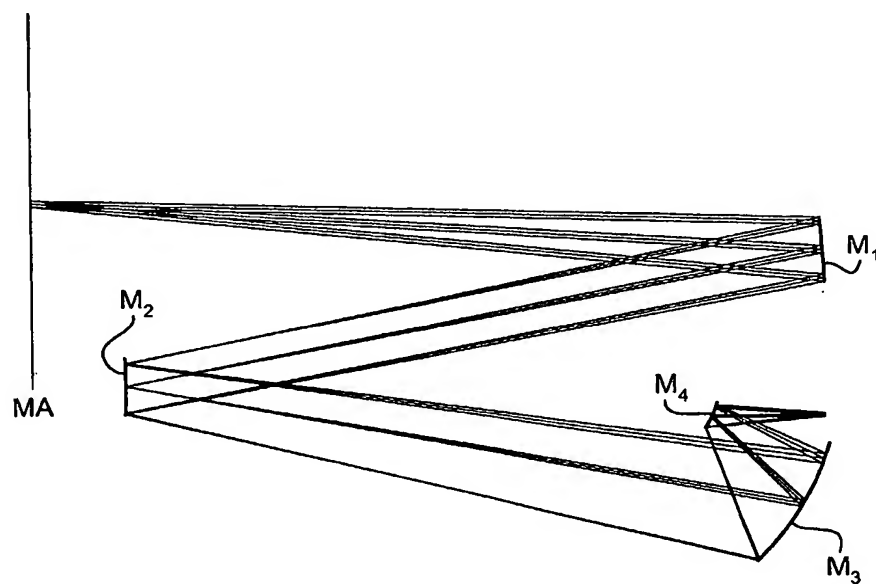


Fig. 11

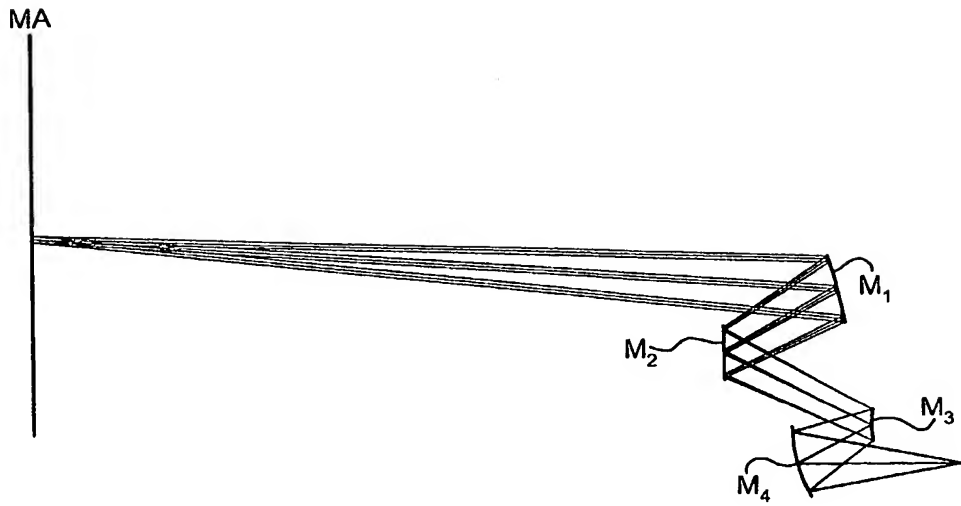


Fig. 12

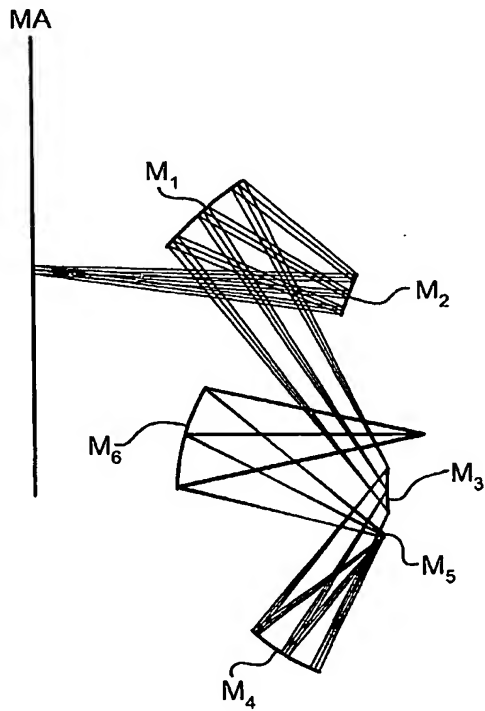


Fig. 13

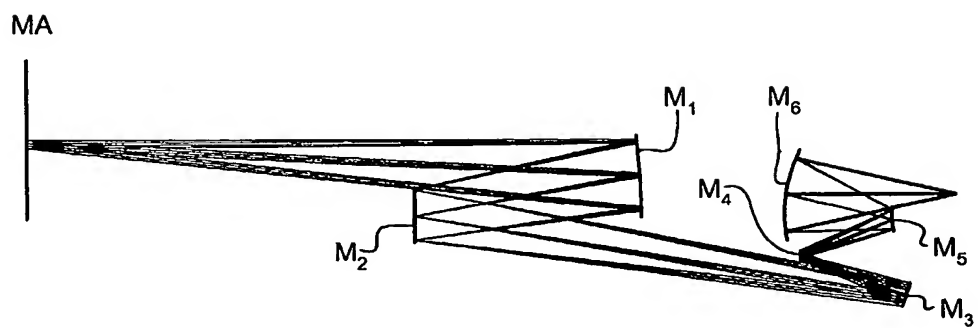


Fig. 14

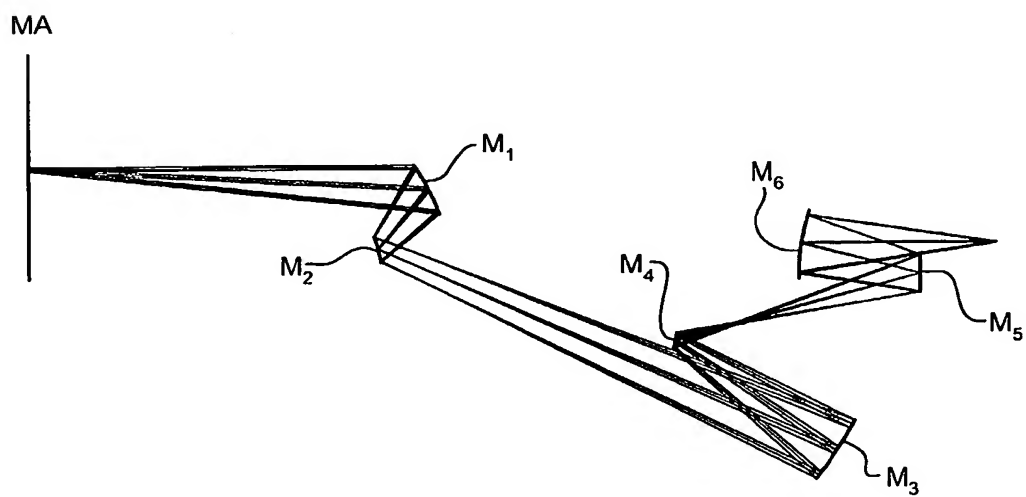


Fig. 15

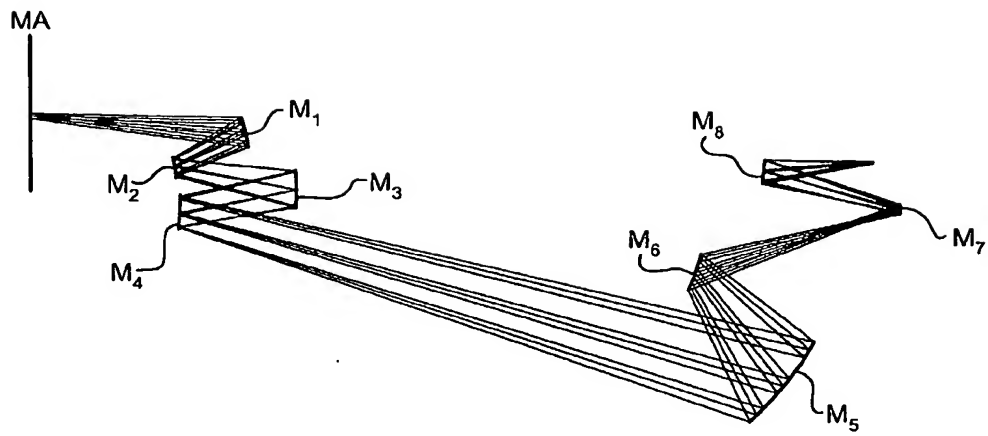


Fig. 16

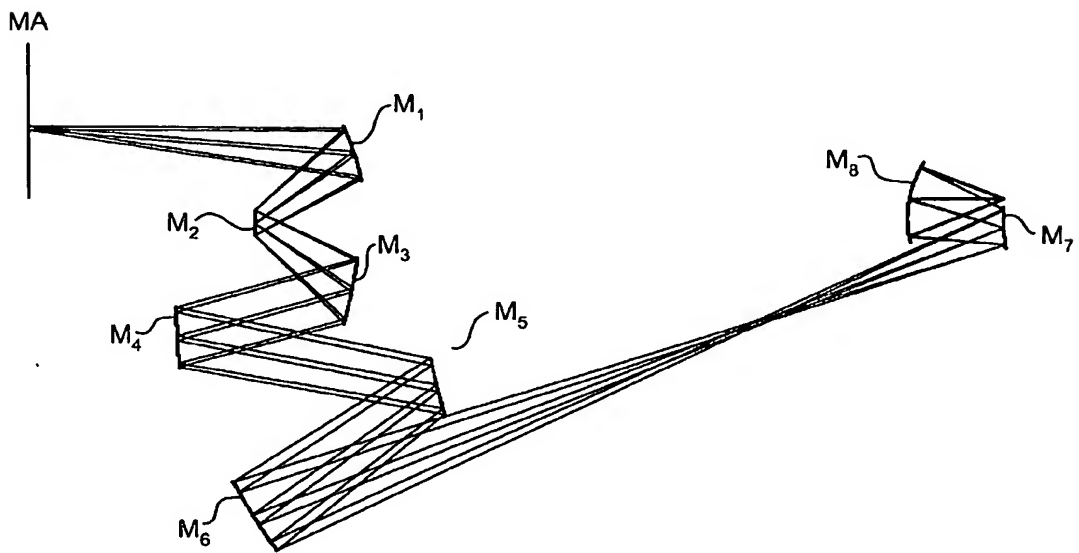


Fig. 17

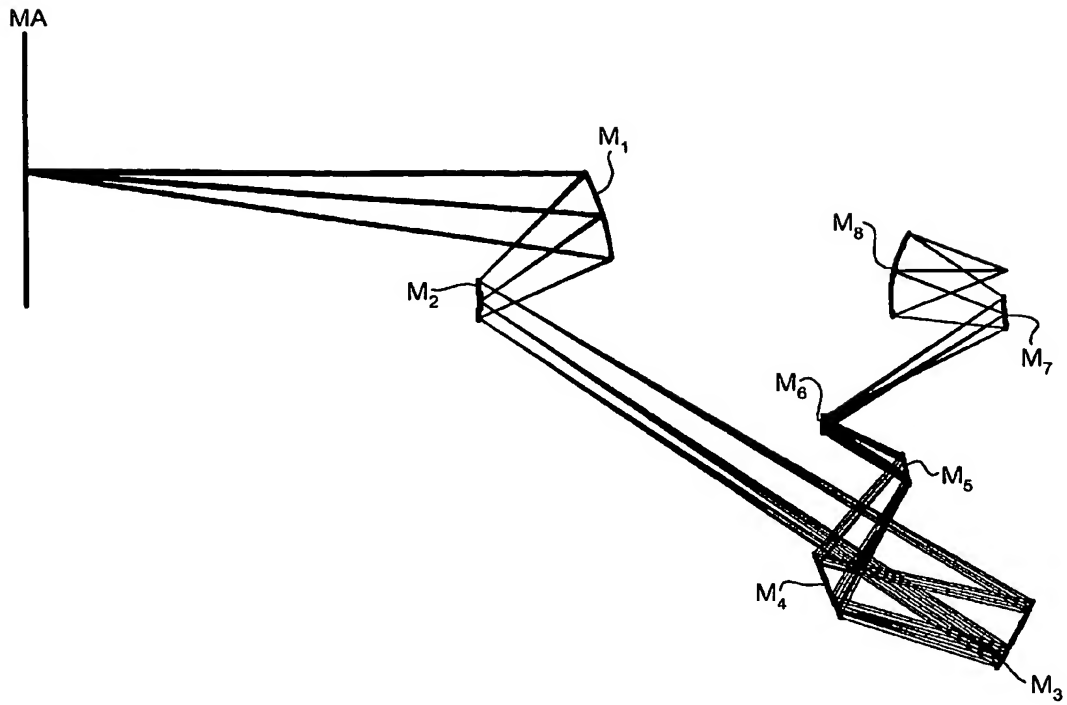


Fig. 18

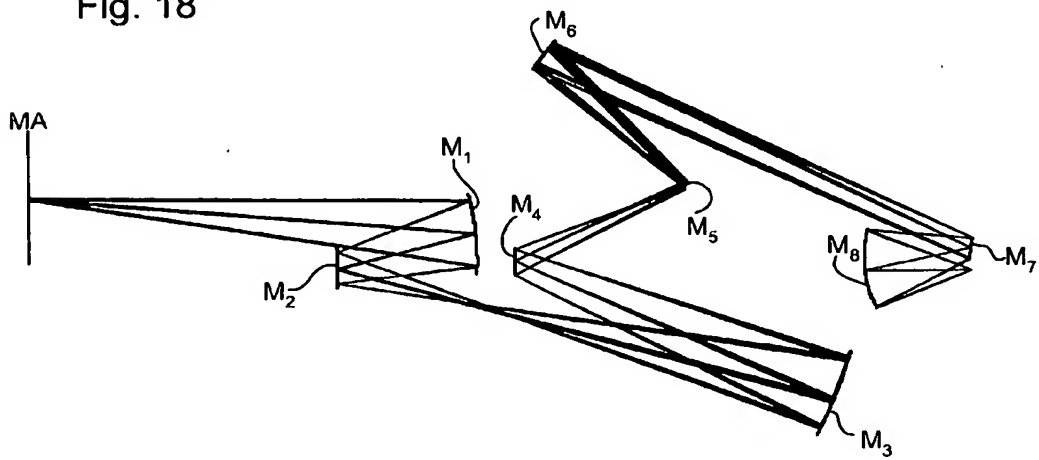


Fig. 19

